

Electron Diffraction Techniques

J. M. Zuo

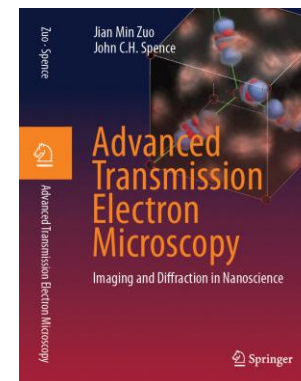
Dept. of Materials and Engineering and Materials
Research Laboratory

University of Illinois at Urbana and Champaign
1304 W Green Street, Urbana, IL61801

jianzuo@illinois.edu

Reference

Advanced Transmission Electron Microscopy,
Imaging and Diffraction In Nanoscience, Zuo
and Spence, Springer, 2017



Electron Diffraction Workshop, Trondheim, Norway, 2017



Covered Topics

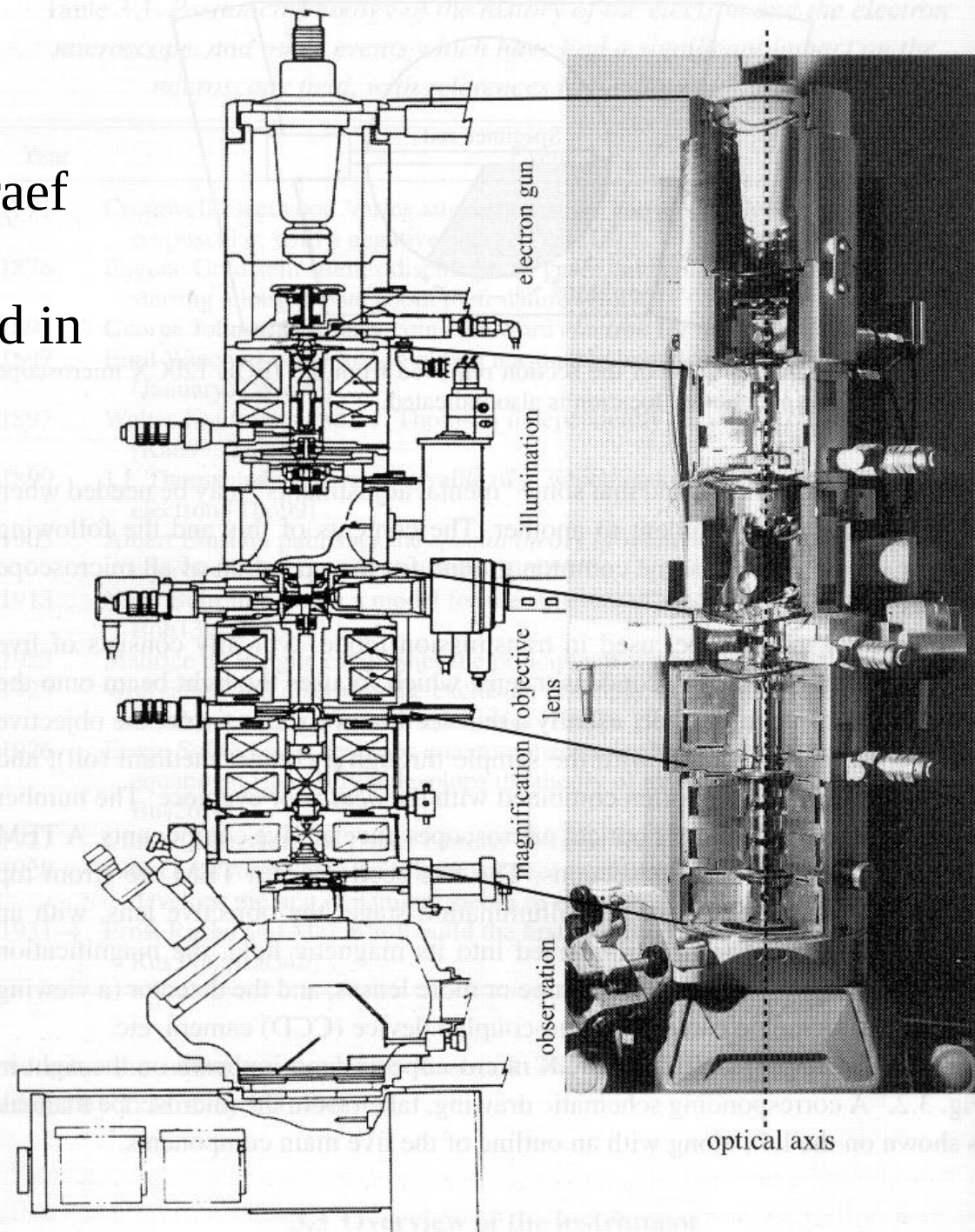
- **Electron diffraction techniques**
 - **Selected area electron diffraction**
 - **Convergent beam electron diffraction**
 - **Large angle methods**
 - **Precession electron diffraction**
 - **Nanoarea electron diffraction**
 - **Scanning electron nanodiffraction**
- **Energy-filtering**
- **STEM, Ronchigram, Position averaged CBED**
- **Electron illumination**
 - **Beam current**
 - **Probe size**
 - **Coherence**
- **Electron detectors and radiation effects**

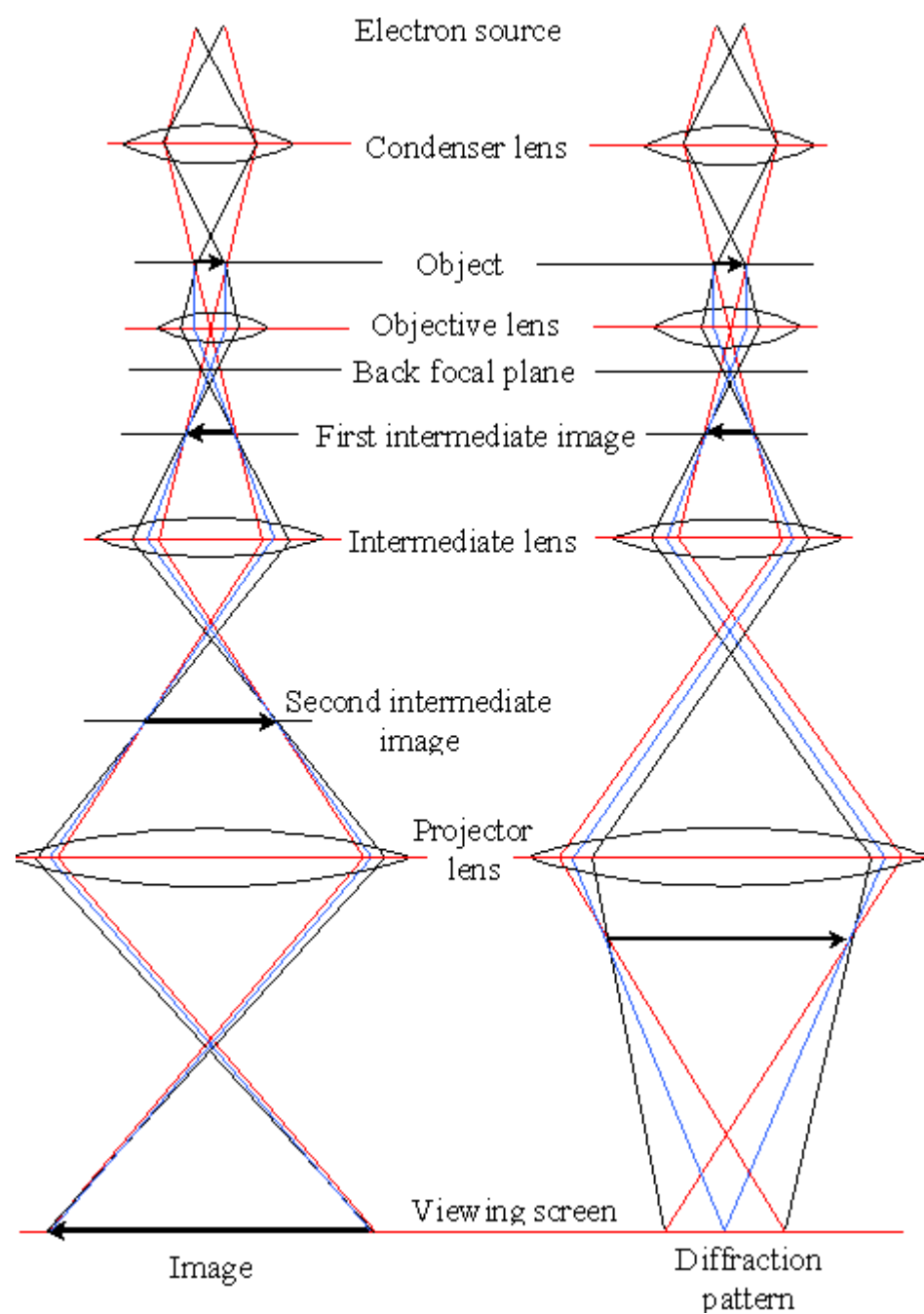


JEOL 120 CX

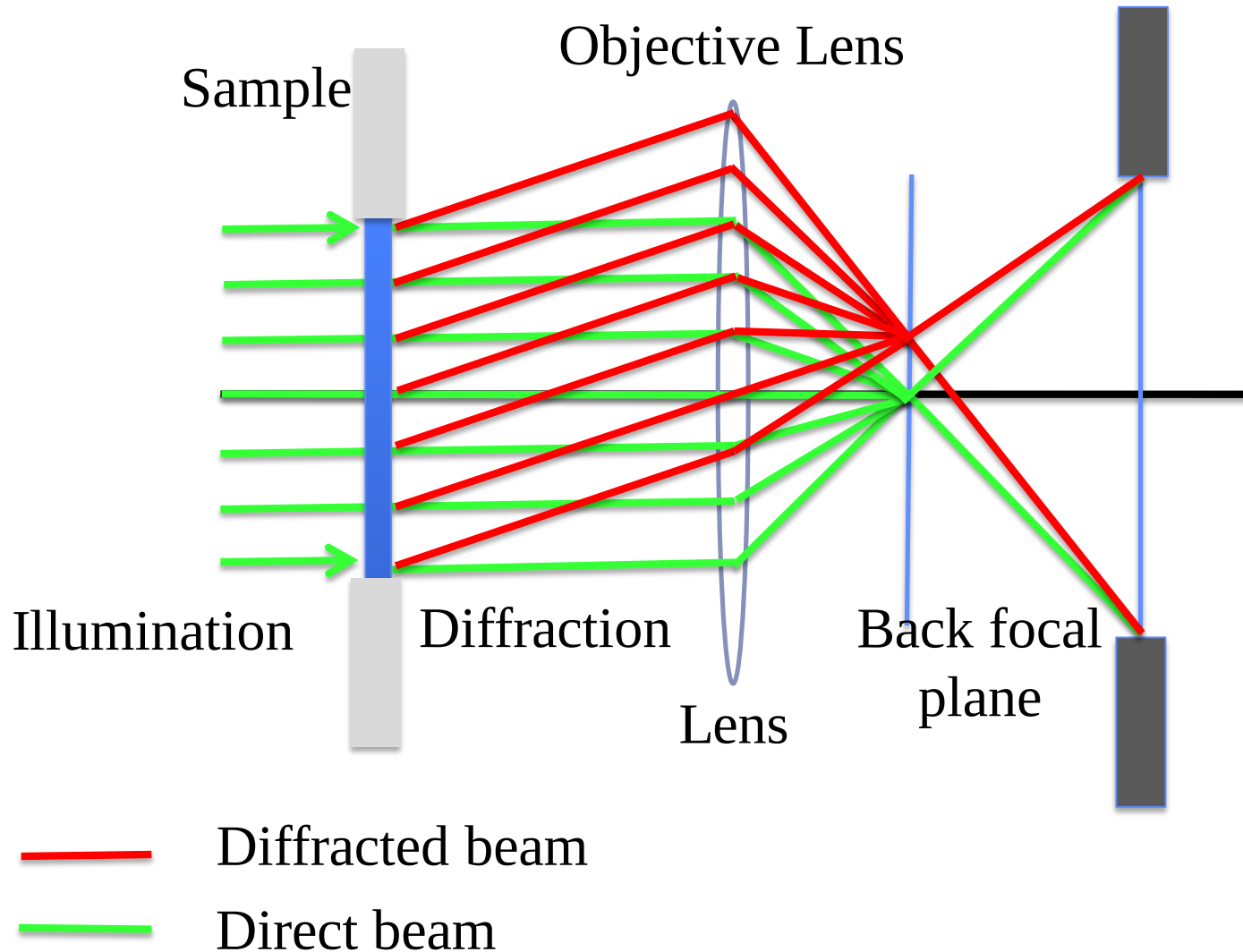
From Marc De Graef

Developed and sold in
early 80s

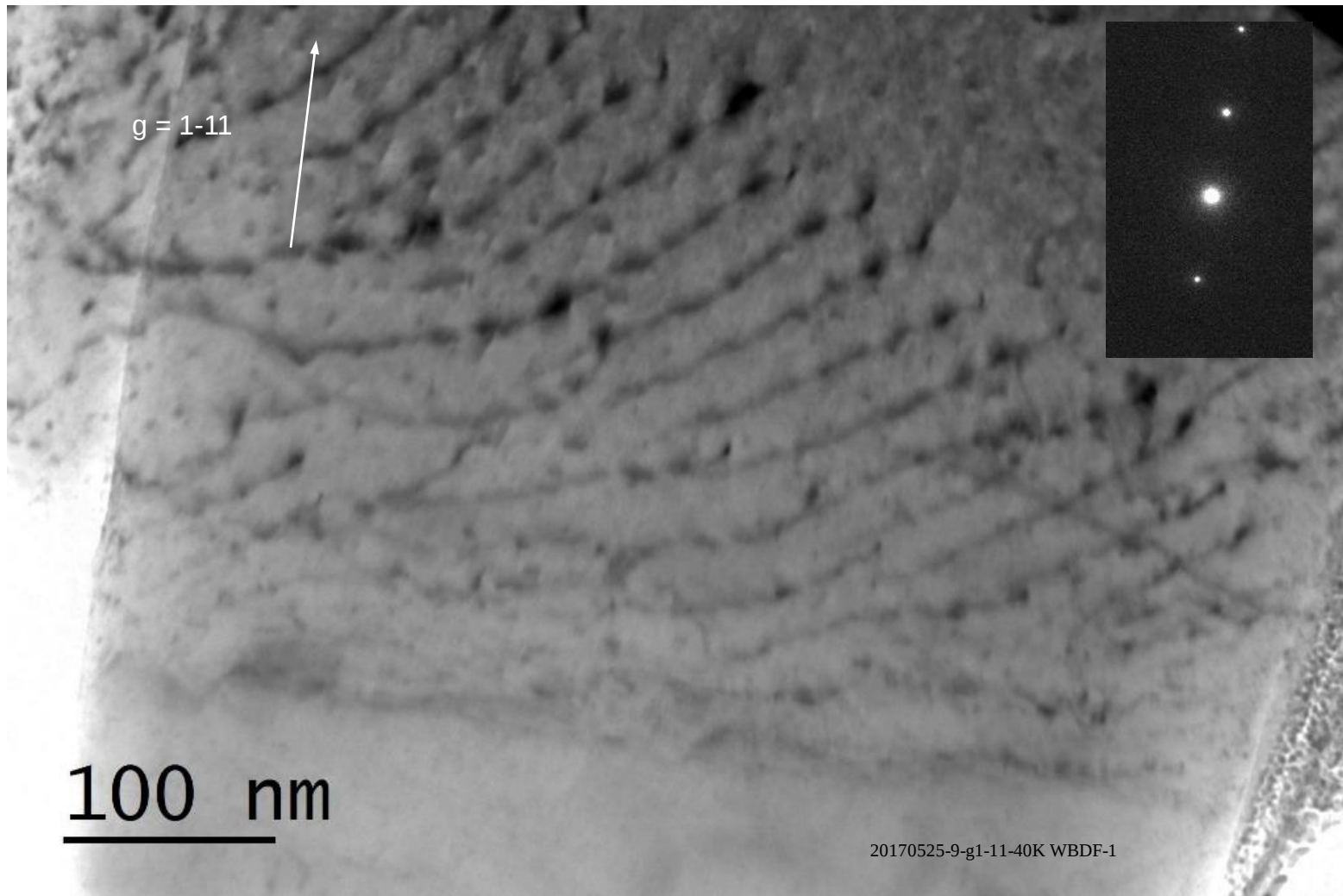




Formation of Diffraction Patterns



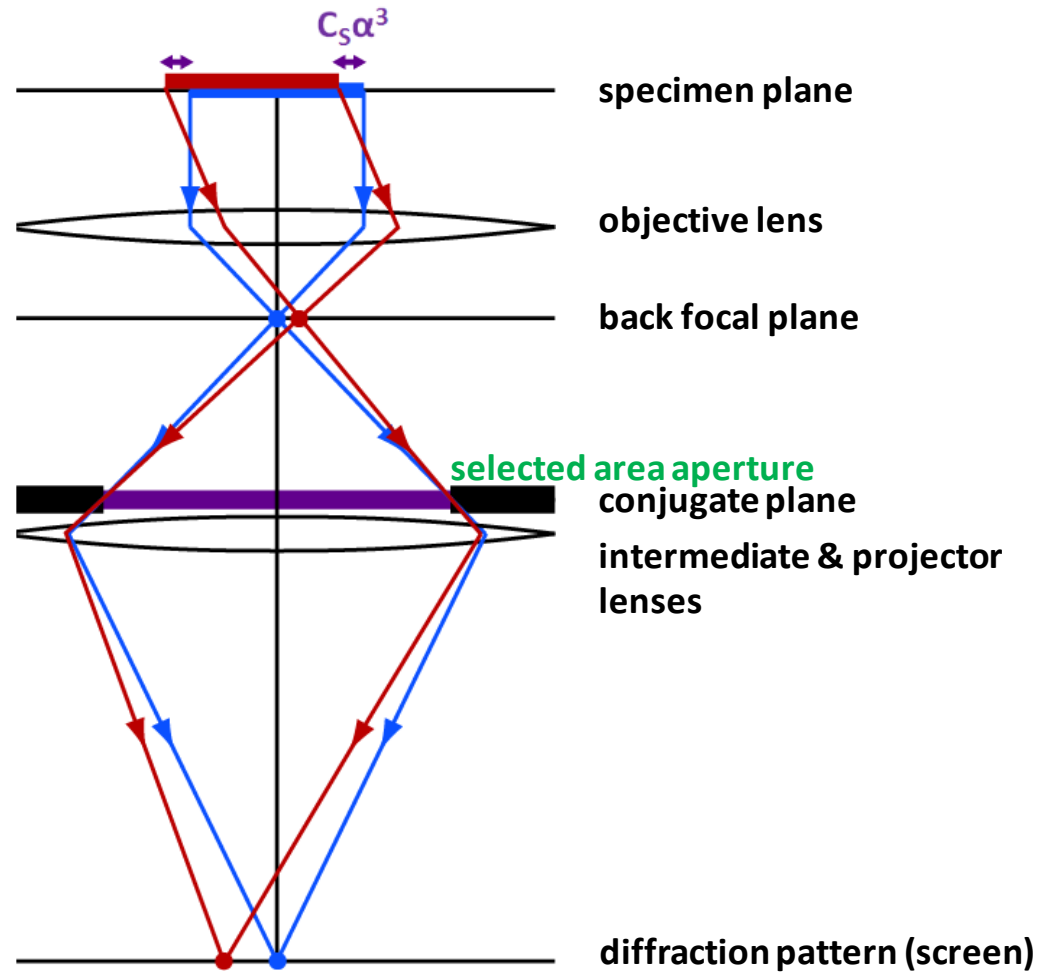
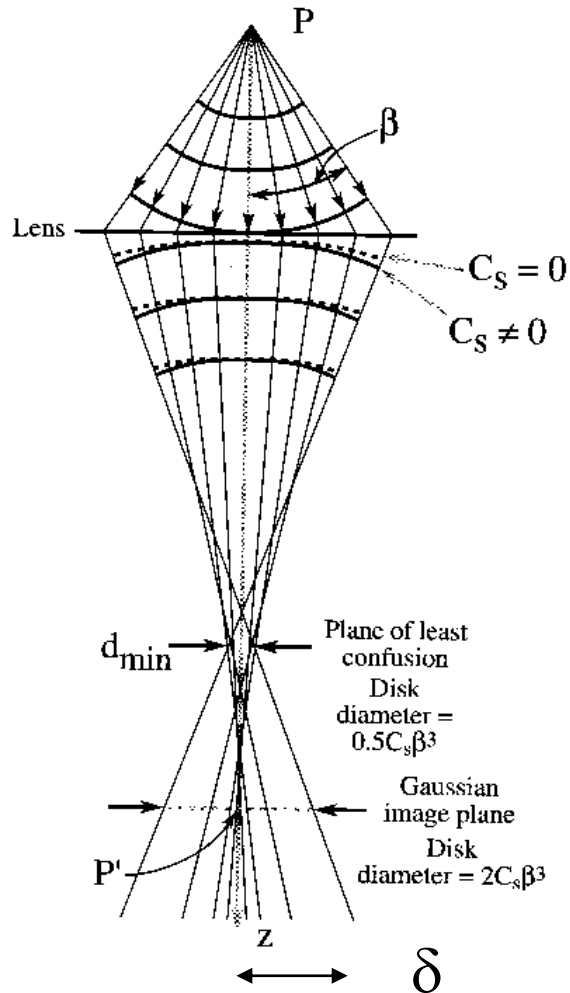
Diffraction Contrast Imaging



From Qun Yang, UIUC

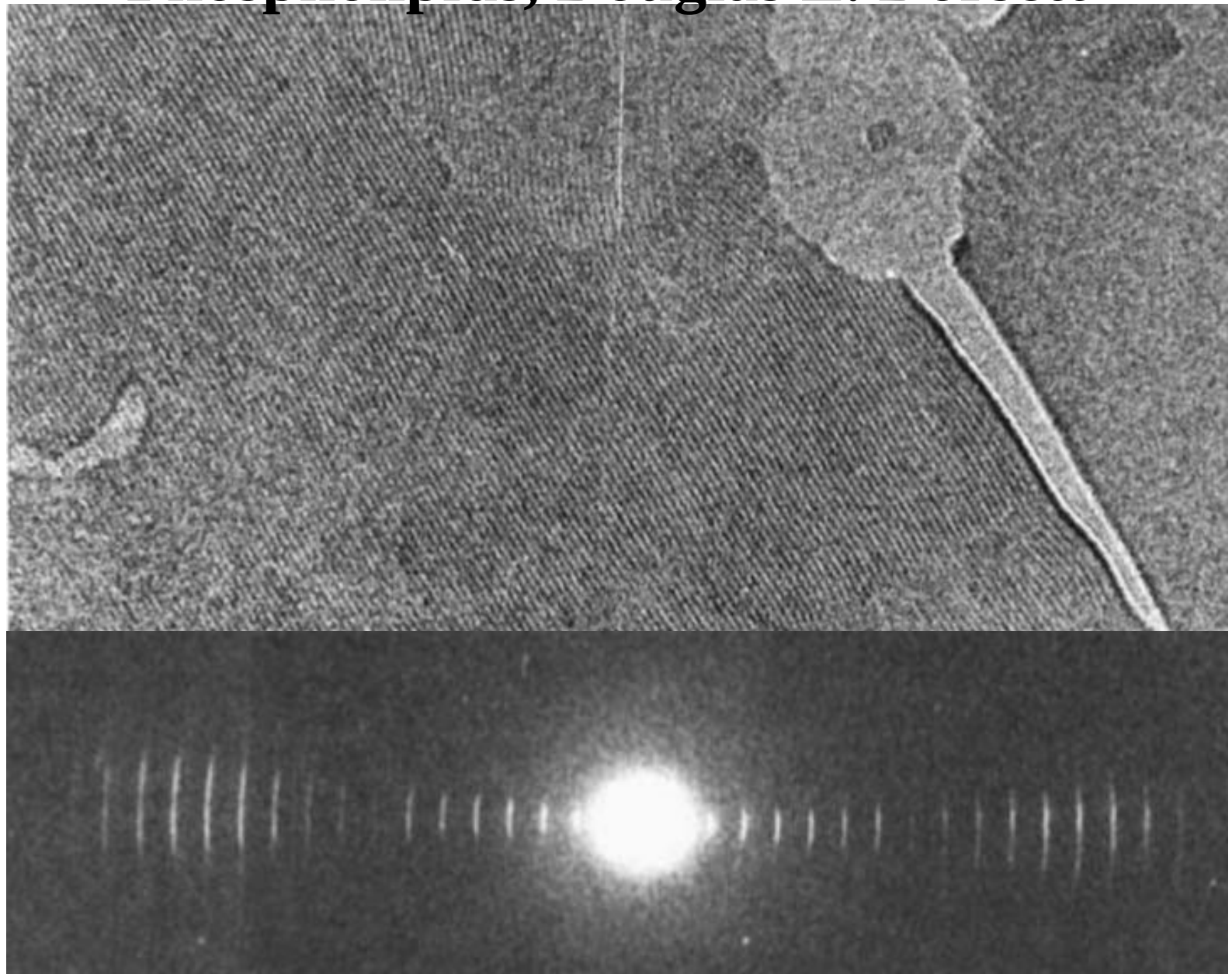


Effects of Spherical Aberration



Provided by Jun Yamasaki of Nagoya University, Japan

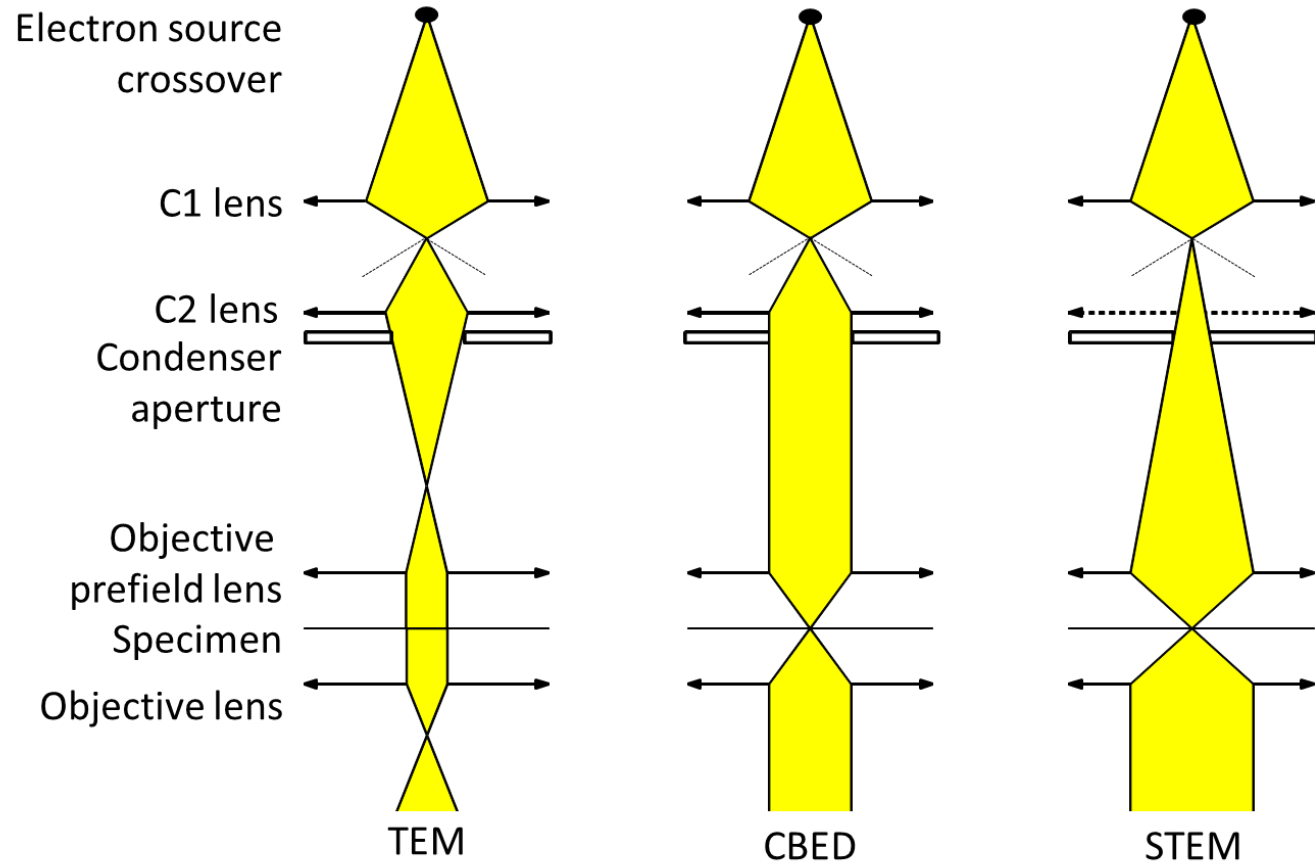
Phospholipids, Douglas L. Dorsett



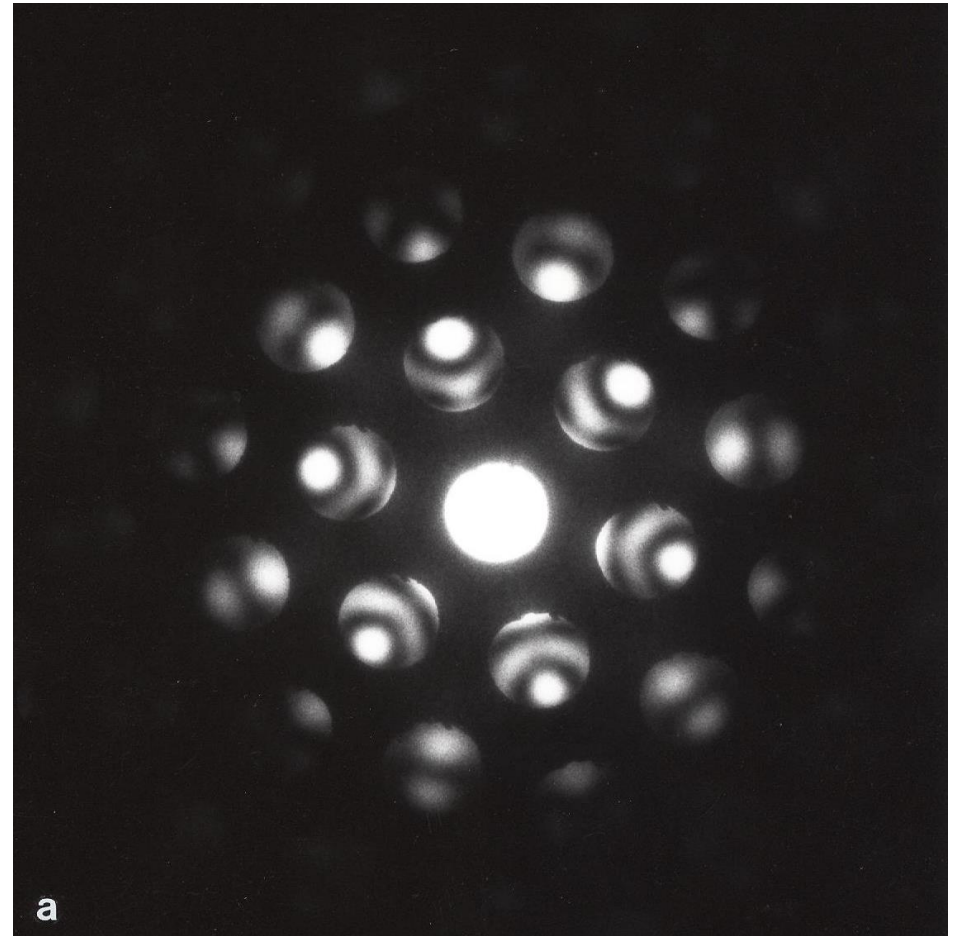
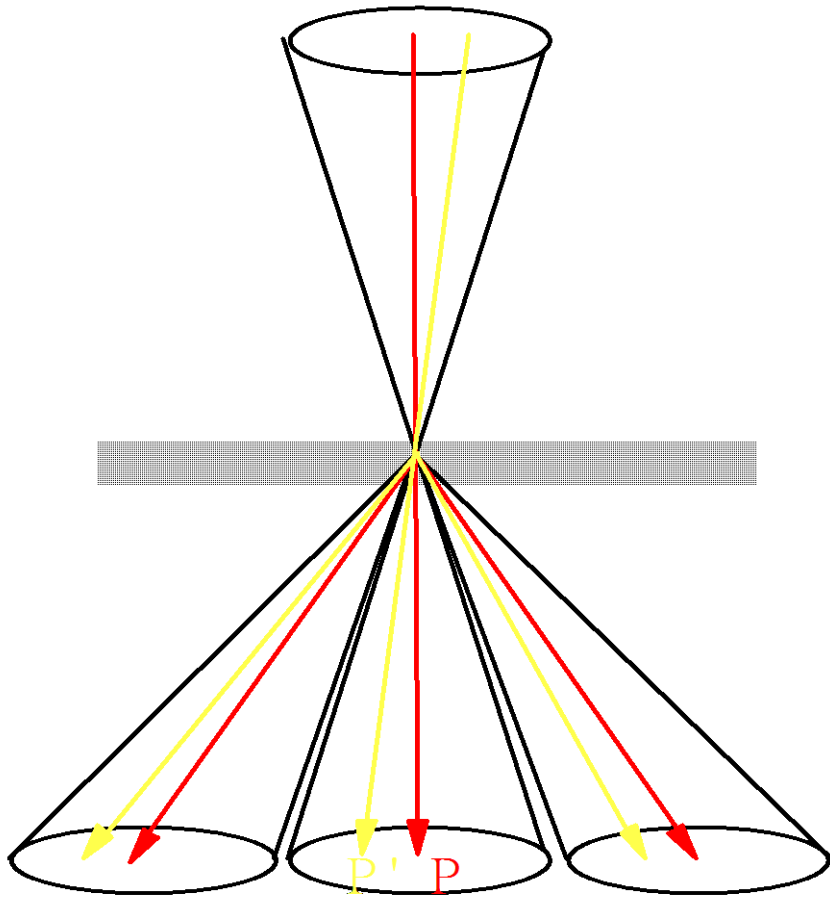
The use of condenser-objective lens



Philips EM400T

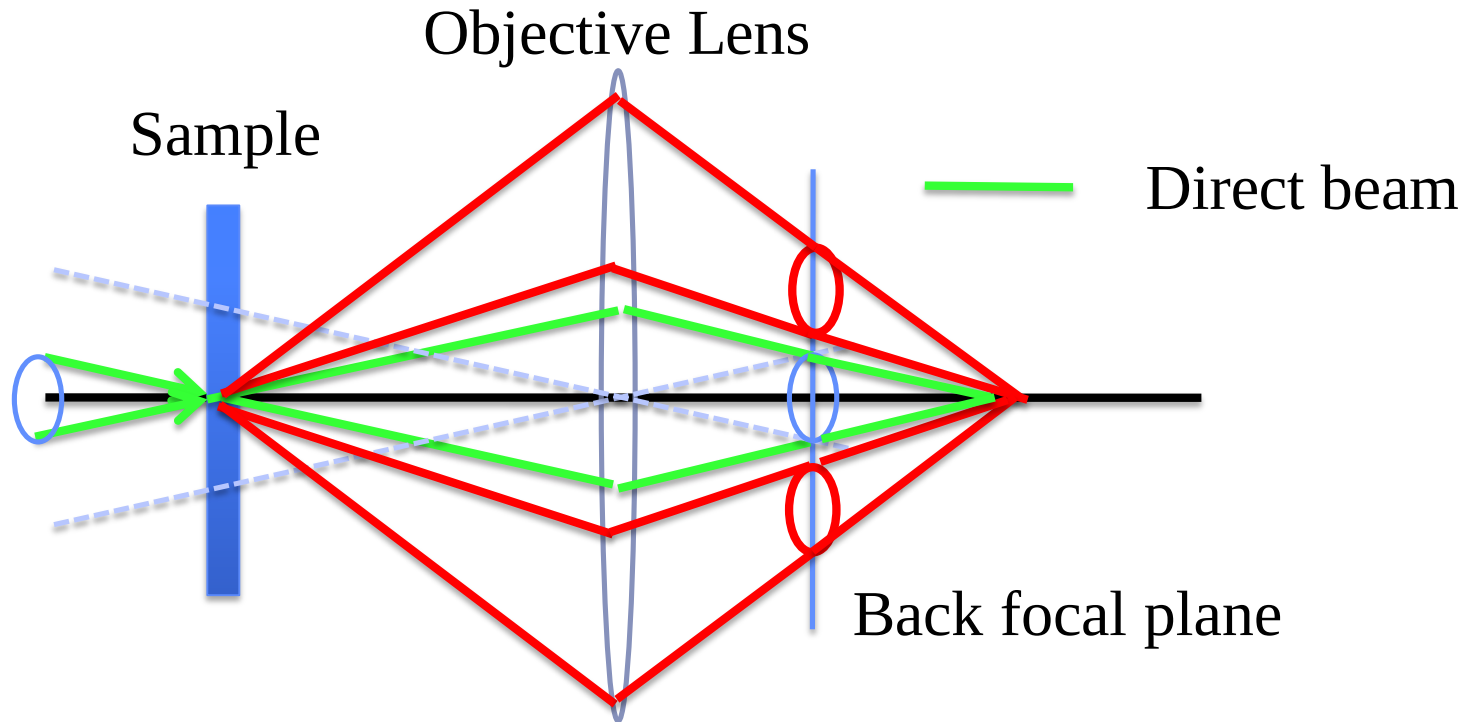


Convergent-beam electron diffraction

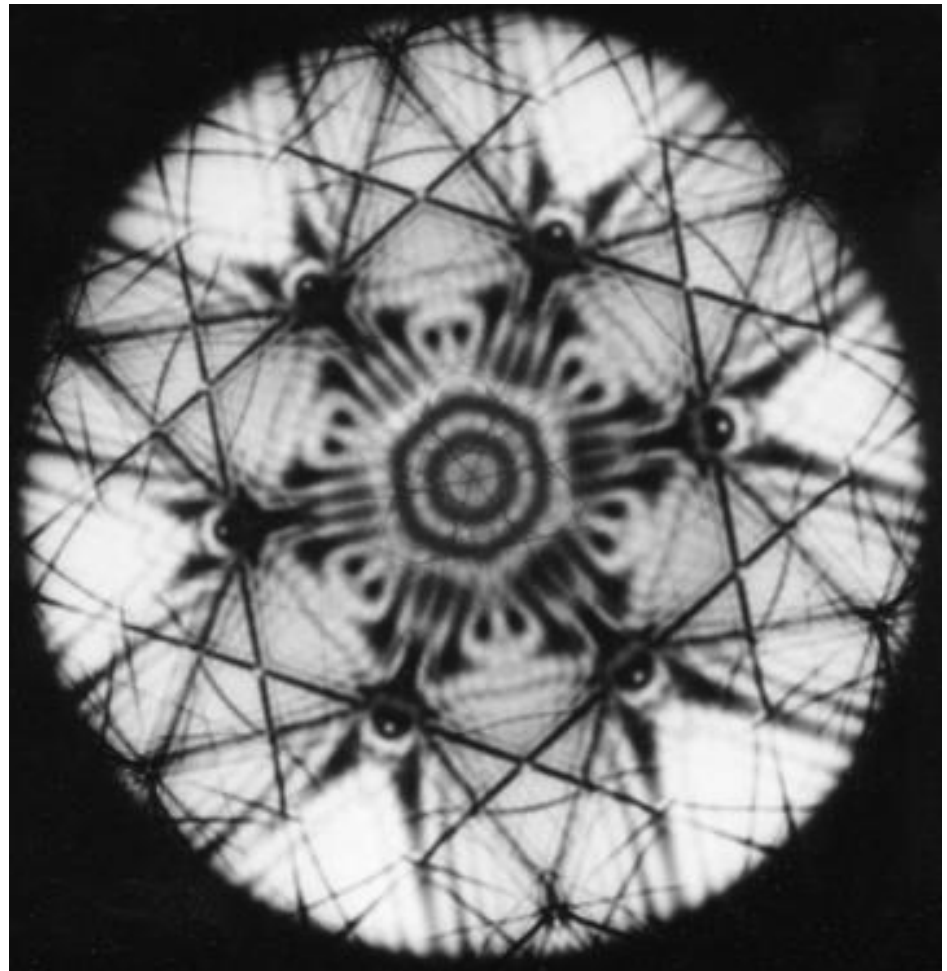
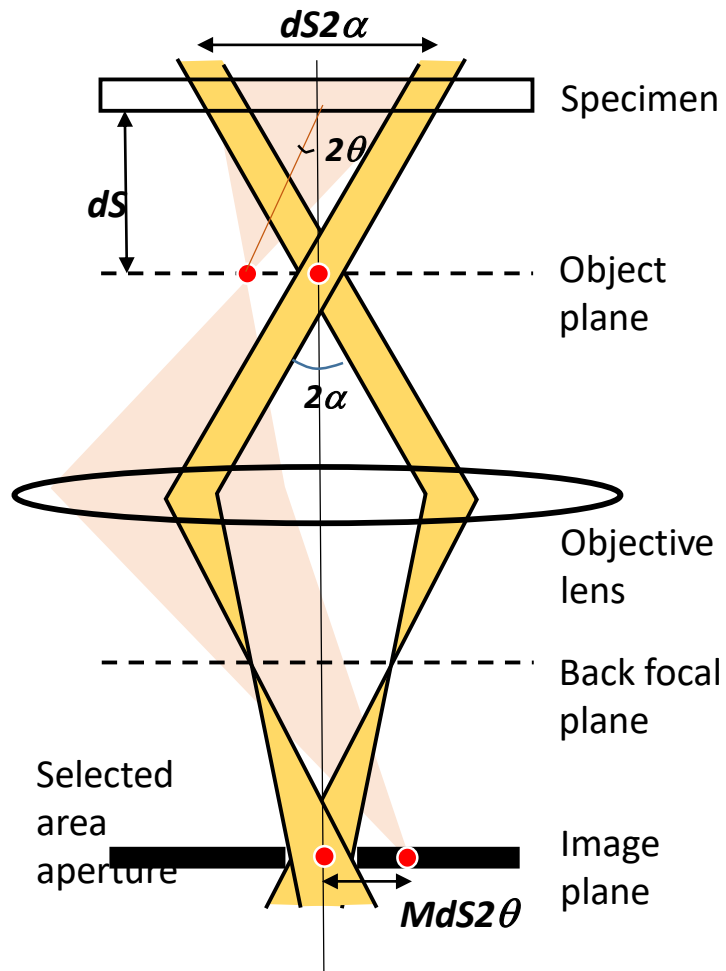


BeO CBED pattern recorded at 100 kV

Lens Action for CBED

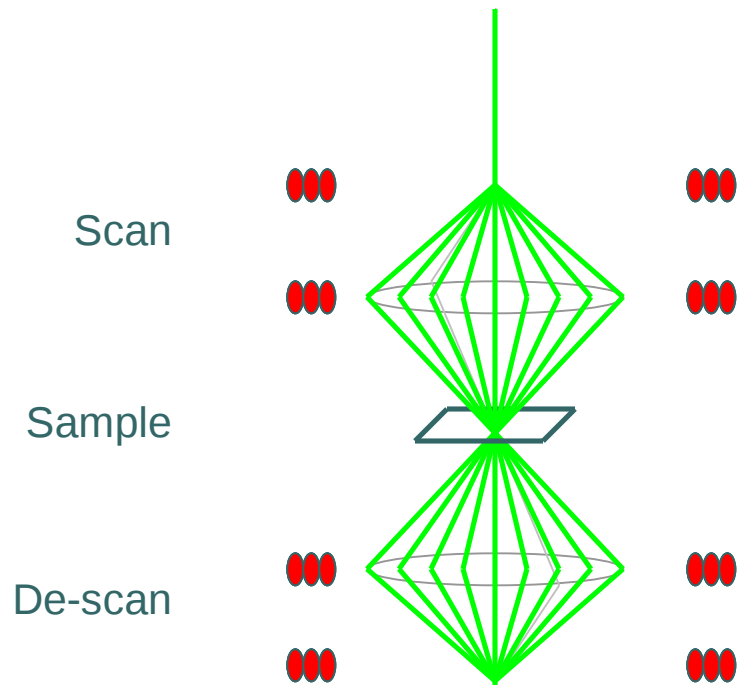


Large Angle CBED



Si <111> 120keV, From John Steeds, Bristol

Vincent-Midgley Precession Method

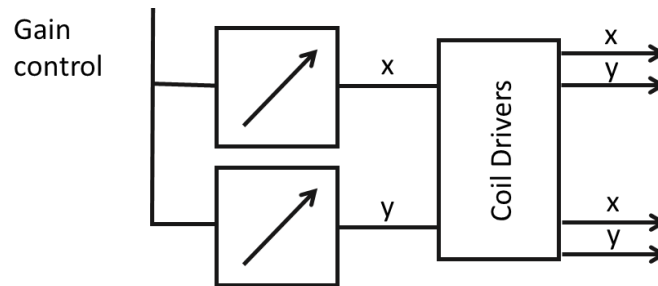
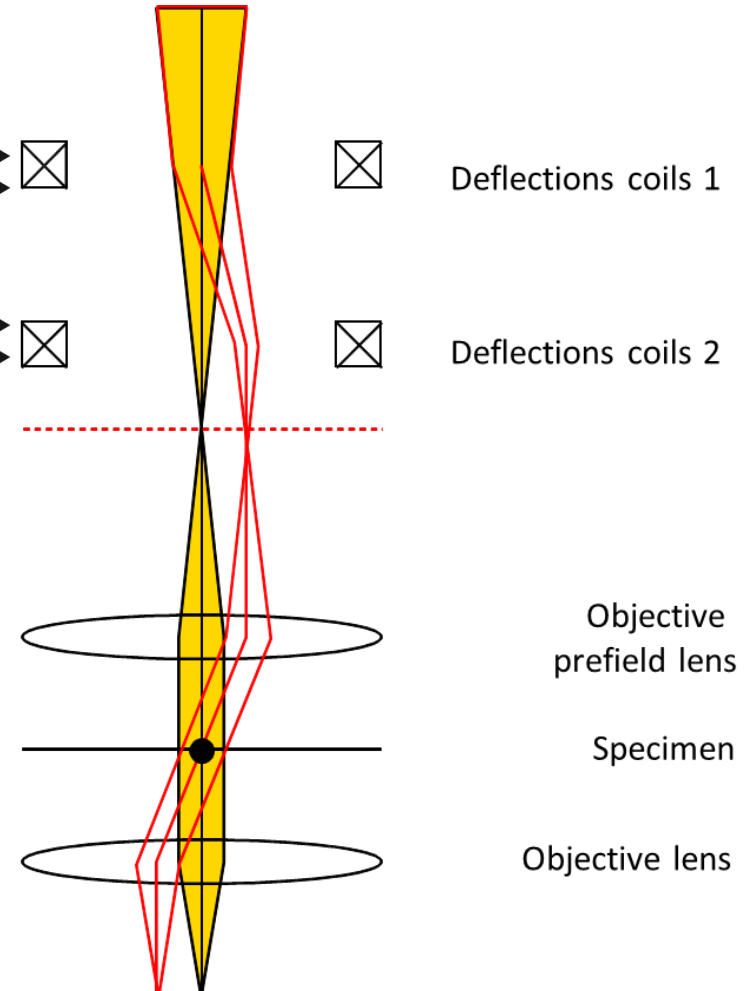
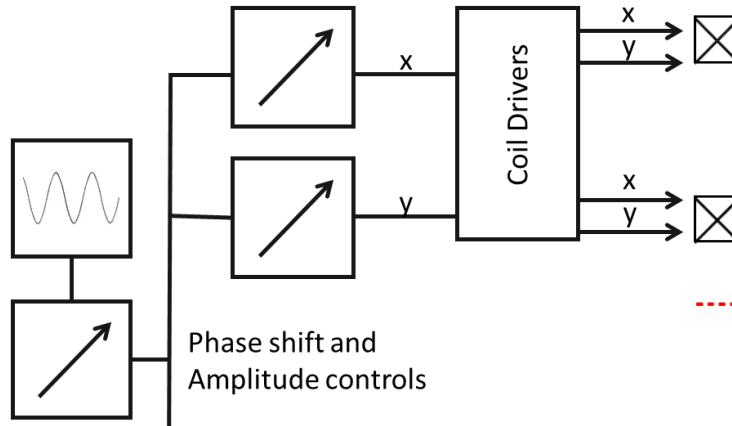
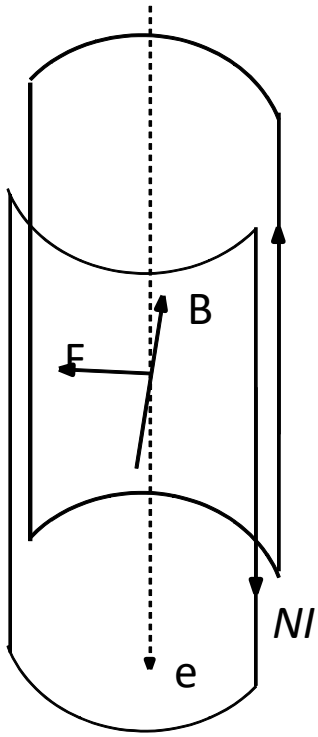


Non-processed

Processed

From Chris Own

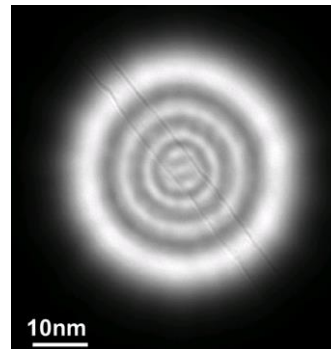
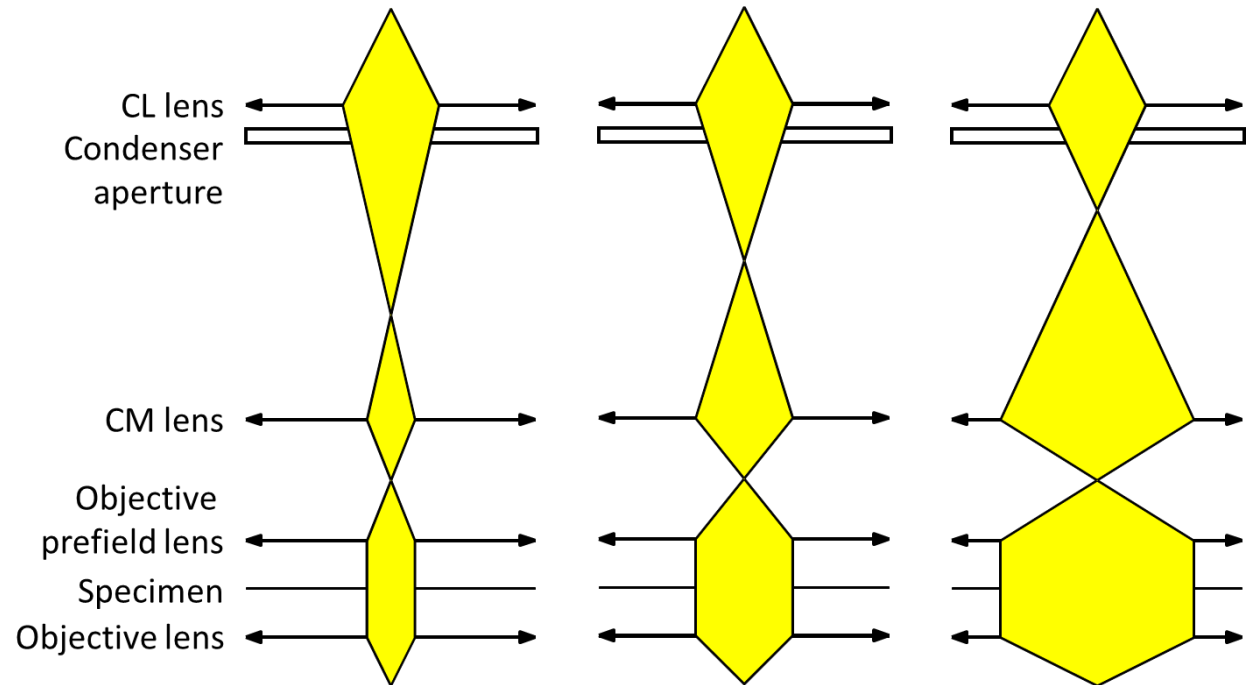
Deflection coils



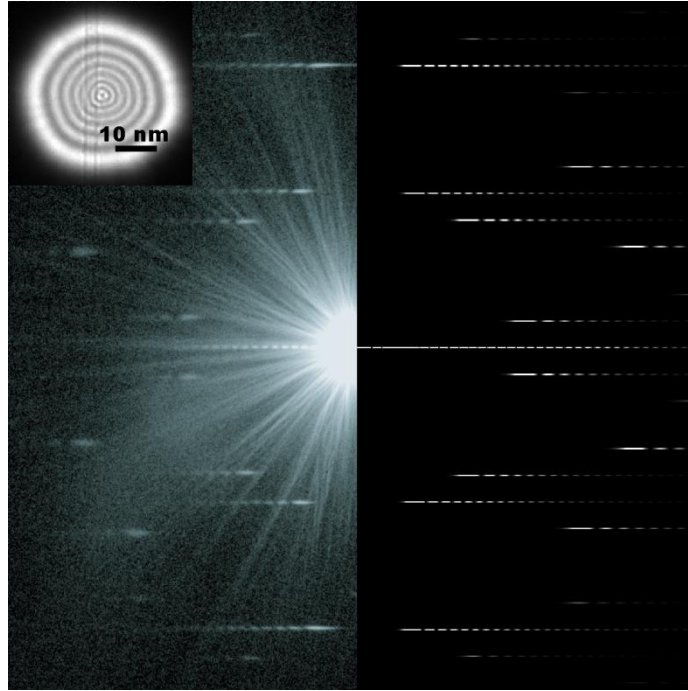
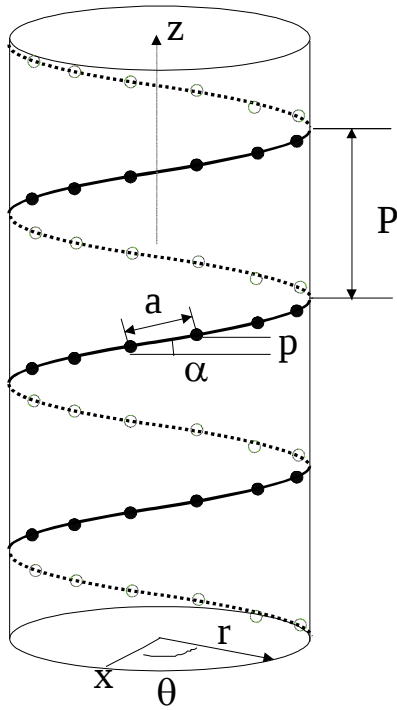
Nanoarea electron diffraction



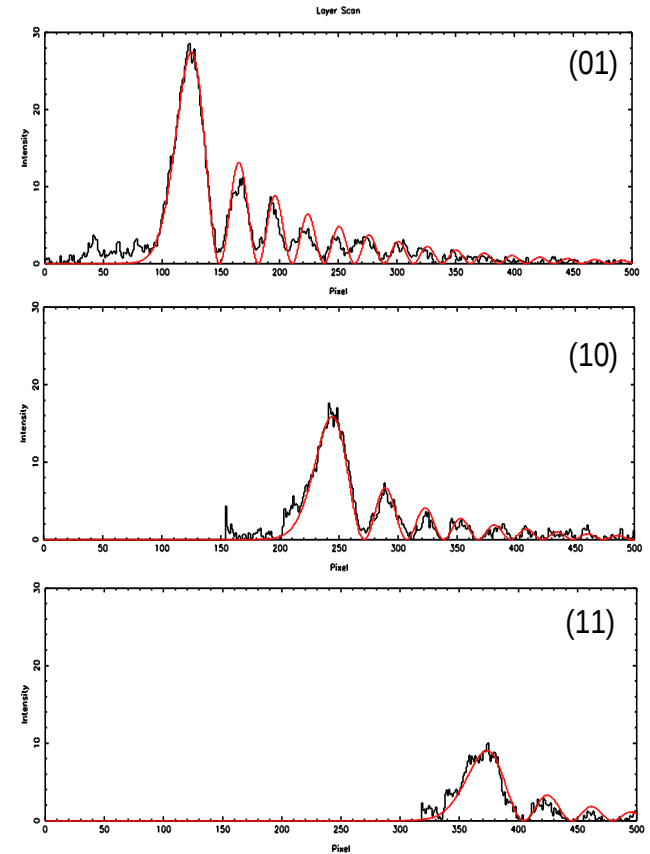
JEOL 2010F



Diffraction of A Single Carbon Nanotube



$D = 34.4 \text{ \AA}$ and $\alpha = 19.53^\circ$



Gao et al, APL, 2003 and Zuo et al. Z. Krist. 2008

Au trisoctahedra



Table 1. Direction and Angles of Diffraction Streaks for the Small TOH in Figure 3

reflection	points to reflection	facet direction	angle between planes	angle from image/calculation	facets direction from image
$(3\bar{3}\bar{1})$	$(\bar{1}19)$ $(\bar{6}6\bar{2})$	$[\bar{4}410]$ $[\bar{9}9\bar{1}]$	65.0°		
$(3\bar{3}\bar{1})$	$(\bar{1}19)$ (442)	$[\bar{4}410]$ $[\bar{1}\bar{1}3]$	54.7°	55.4° (54.7°)	$[\bar{4}410]$ $[\bar{1}\bar{1}3]$
$(00\bar{4})$	$(\bar{1}\bar{1}\bar{1})$ $(\bar{6}612)$	$[\bar{1}\bar{1}3]$ $[\bar{6}616]$	53.2°		
$(2\bar{2}\bar{4})$	$(\bar{3}3\bar{5})$ $(\bar{5}5\bar{1})$	$[\bar{5}5\bar{1}]$ $[\bar{7}73]$	24.9°		
				61° (64.8°)	$[\bar{1}\bar{1}0]$ $[\bar{1}\bar{1}3]$
				40° (43°)	$[\bar{1}\bar{1}3]$ $[\bar{2}2\bar{8}]$

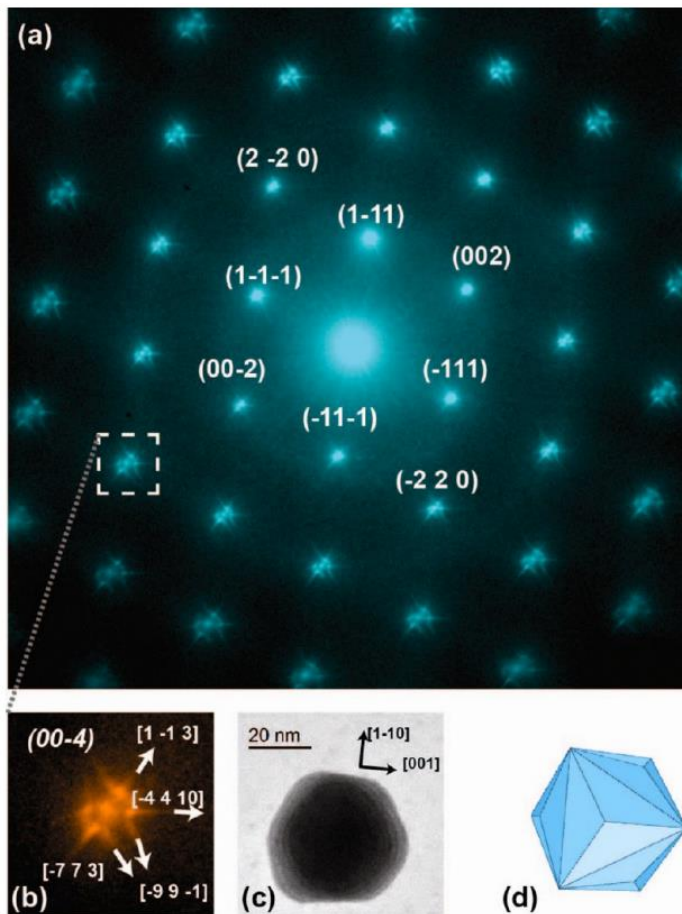
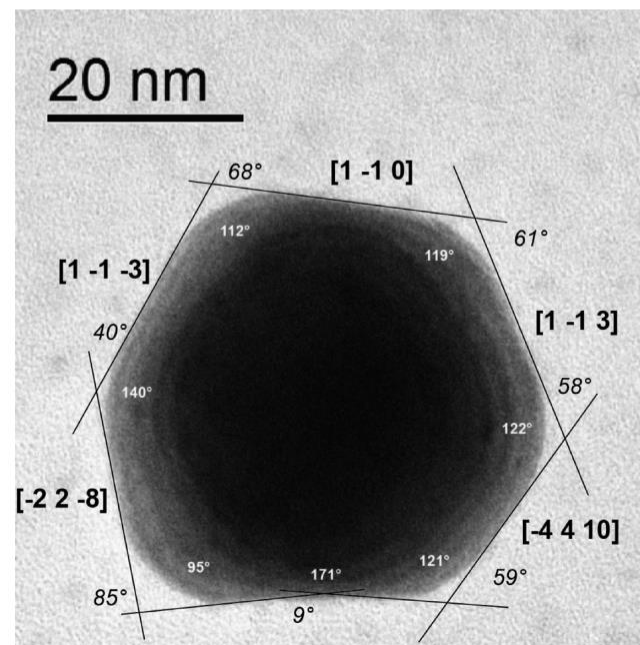
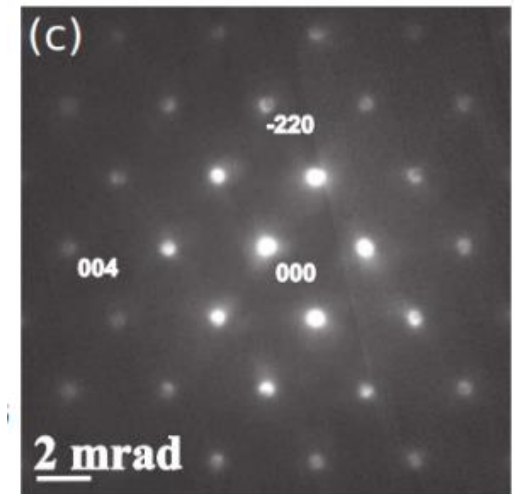
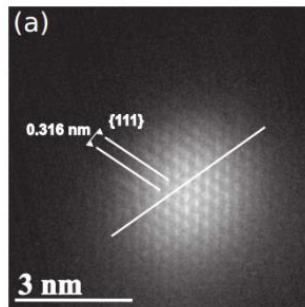
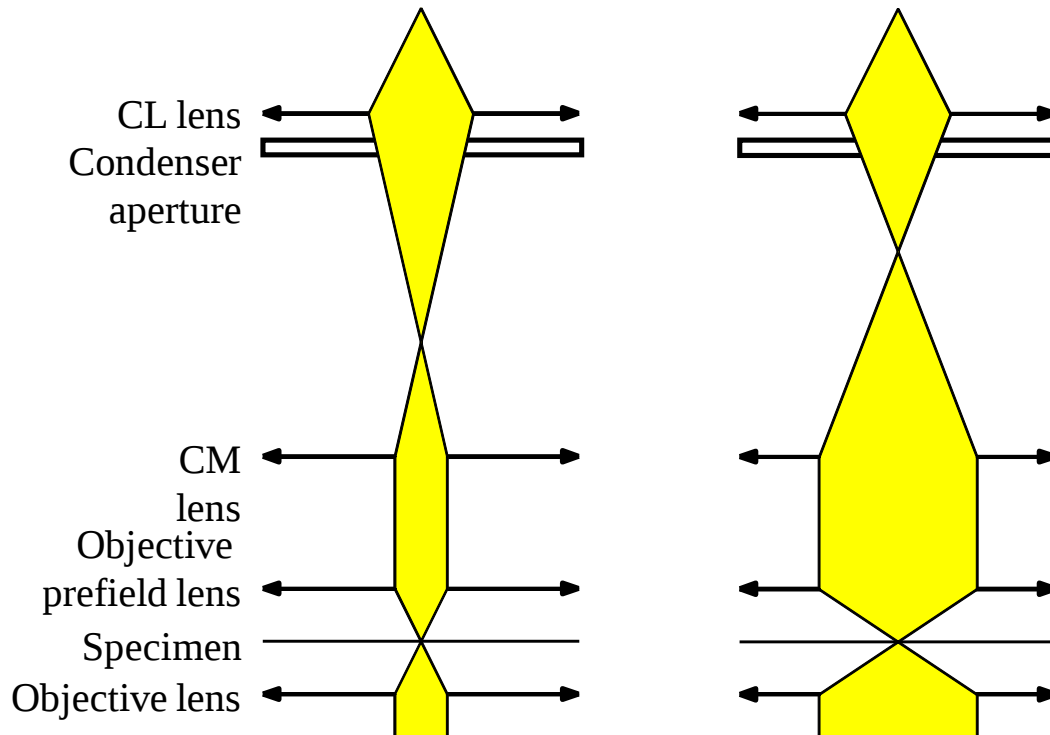


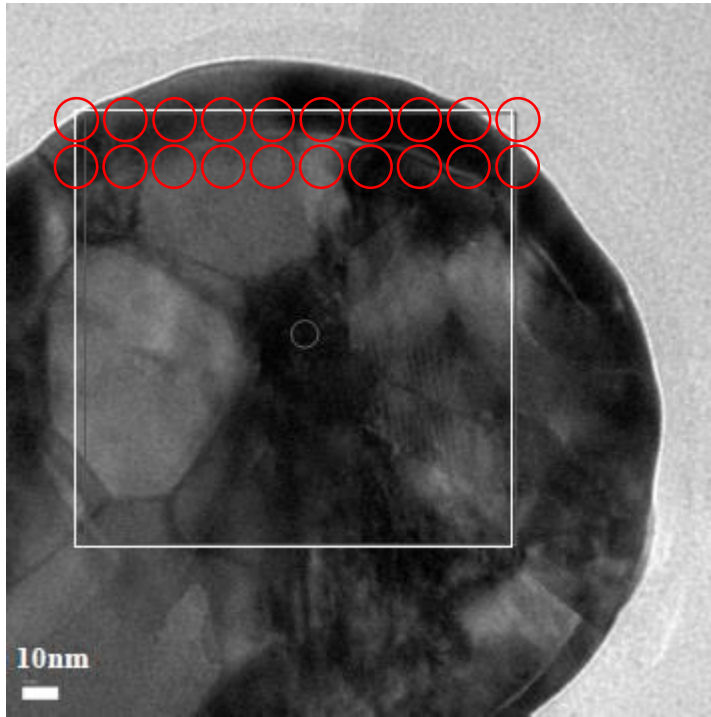
Figure 3. (a) NED pattern of a 44 nm TOH crystal oriented on the $[110]$ zone axis. The streaks are normal to the planes. (b) Magnified view of $(00\bar{4})$ reflection showing streaks measured from this and other reflections. (c) TEM image of the TOH crystal. (d) Computer generated image of the TOH crystal.



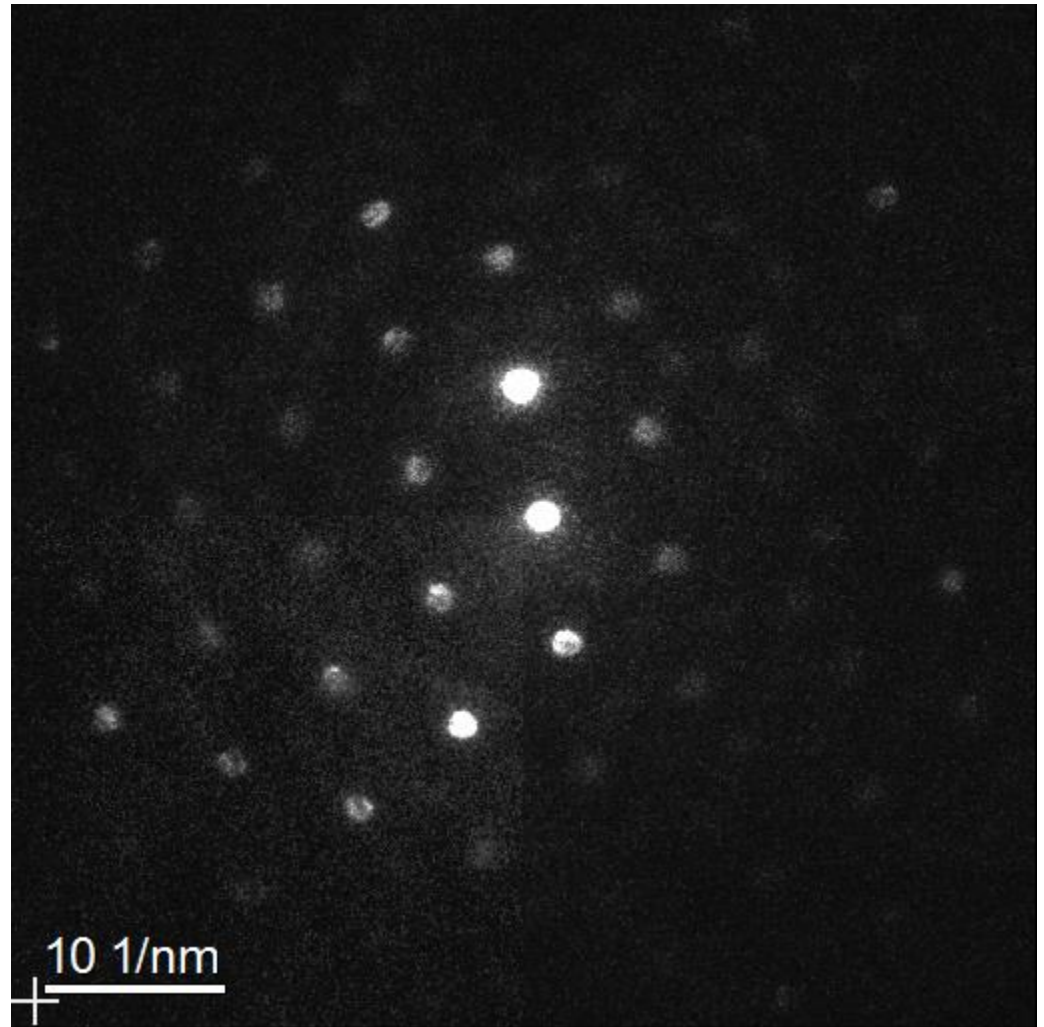
Electron Nanodiffraction



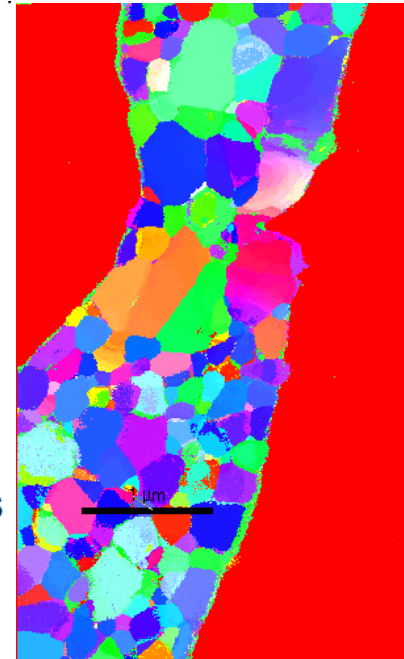
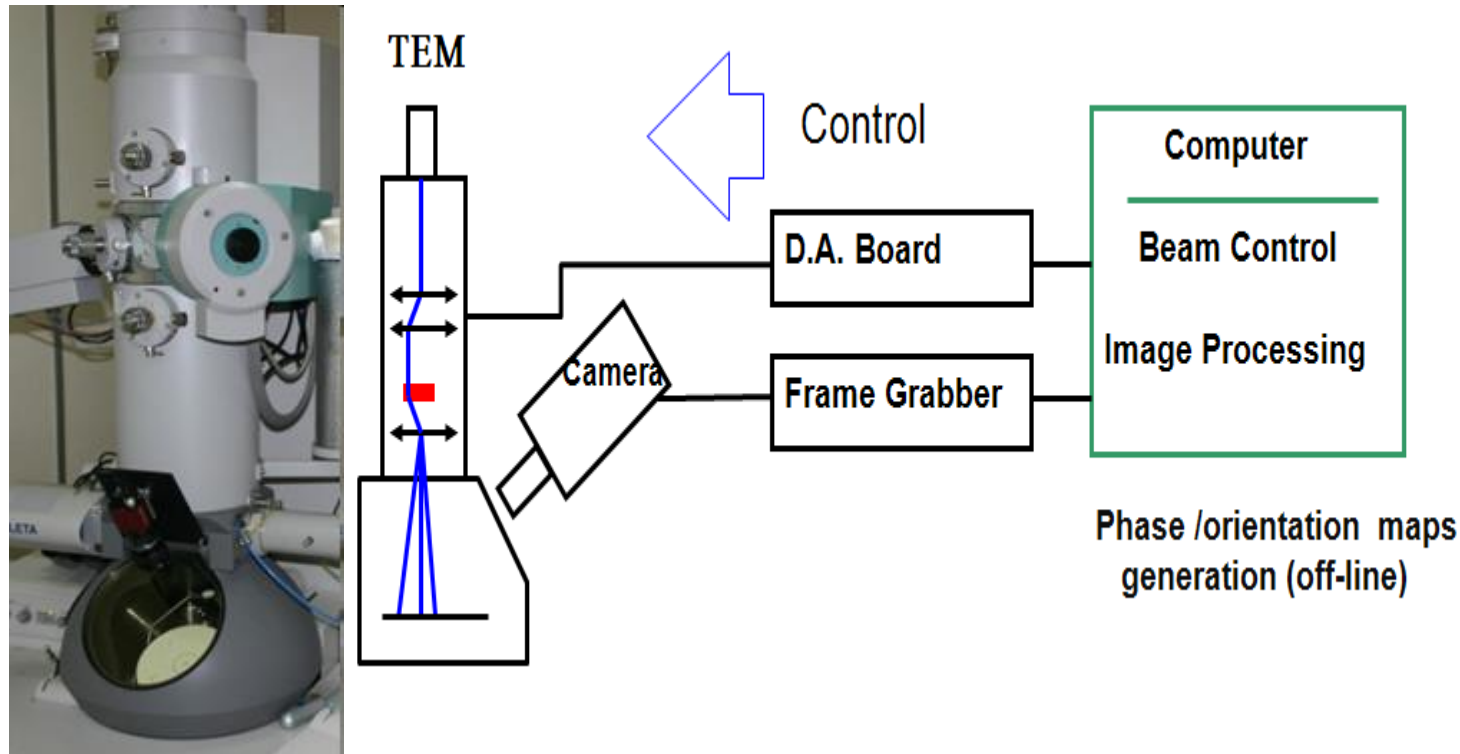
Scanning Electron Nanodiffraction



Cross-section of fabricated Au wire

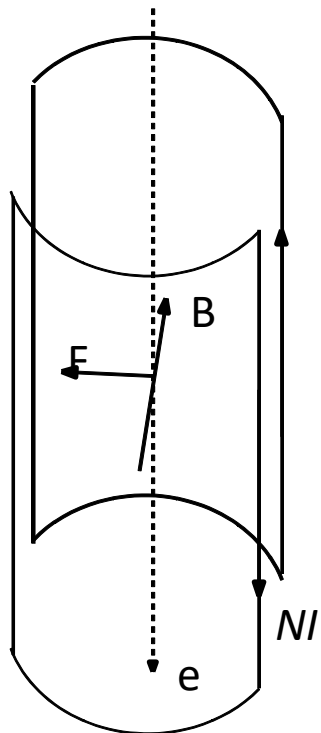


ASTAR (EBSD like capability in TEM)



CM20 UTwin LaB6
Prof . S. Godet
ULB Brussels

Demonstrated Resolution: **15 nm for LaB6**
~1 nm for FEG



Deflections coils 1



Deflections coils 2



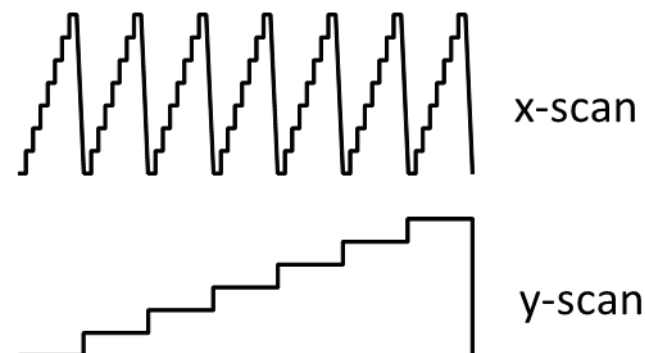
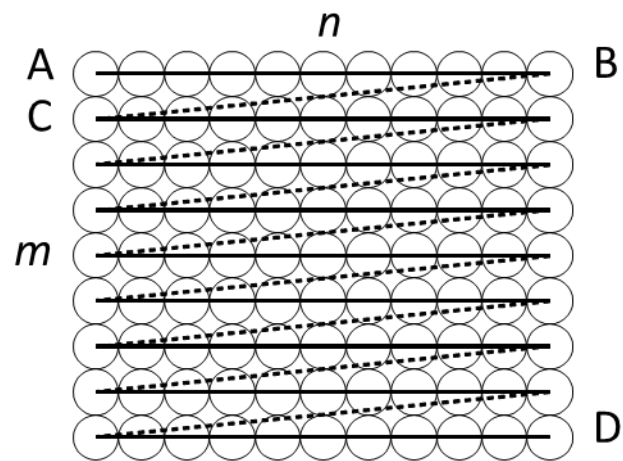
Objective
prefield lens



Specimen



Objective lens



Low Dose Scanning Electron Nanodiffraction (SEND)

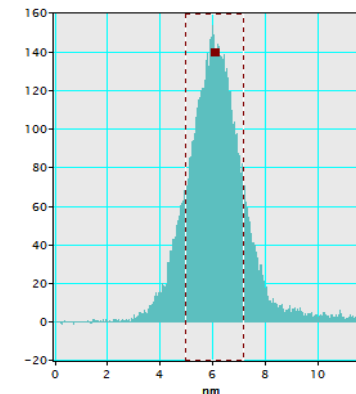
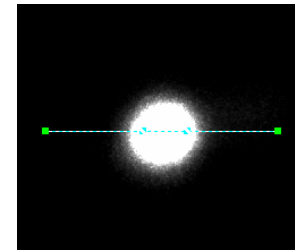
JEOL 2100LaB₆ 80-200 kV



Gatan Ultrascan
2kx2k CCD
Camera



Fiber-optic coupled
14 μm square pixels

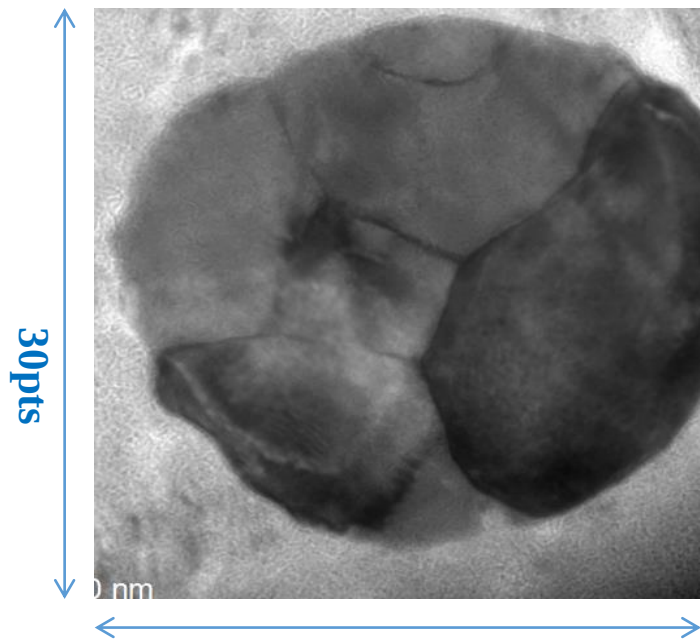


Demonstrated Resolution: **2 nm**
for LaB₆

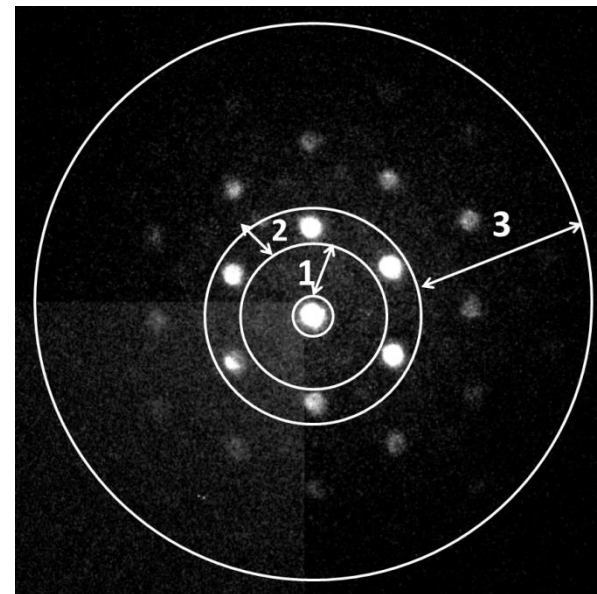
Advantage: Low Dose

$I=0.1$ pA or less

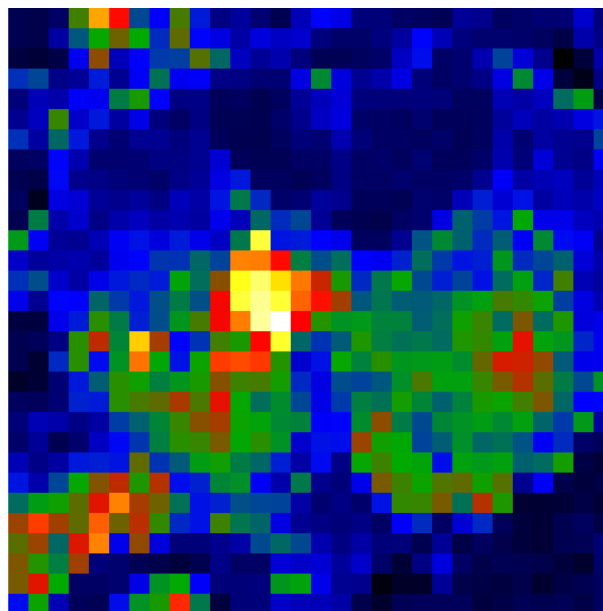
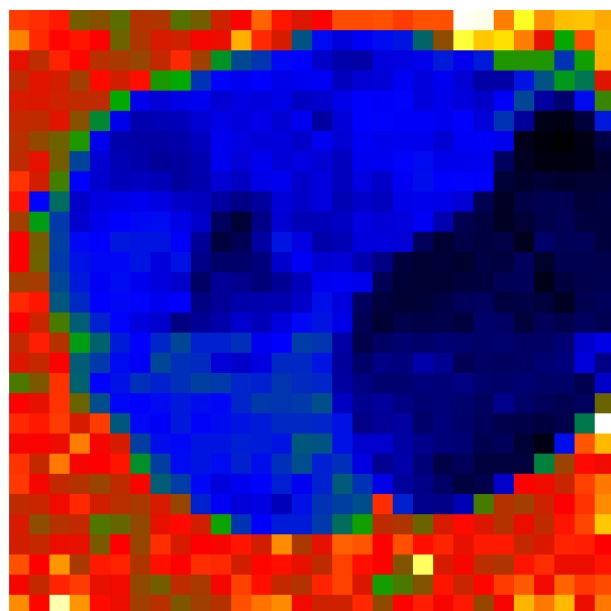
Kim, Kyou-Hyun; Xing, Hui; Zuo, Jian-Min; et al.
MICRON 71, 39-45, 2015



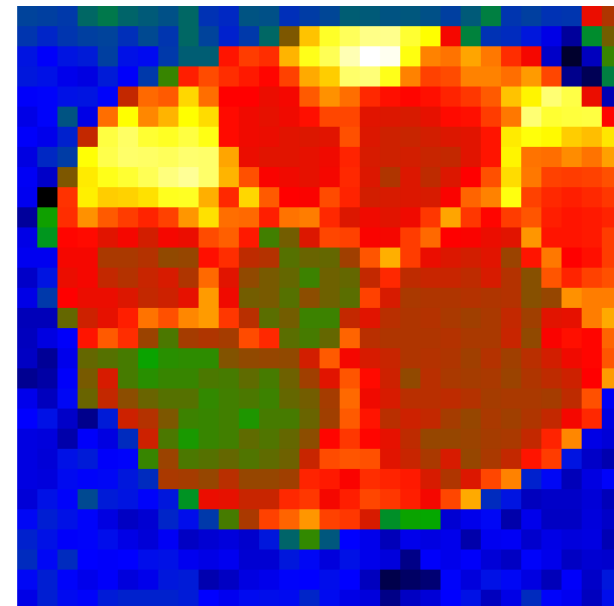
1st Order



2nd Order



3rd Order

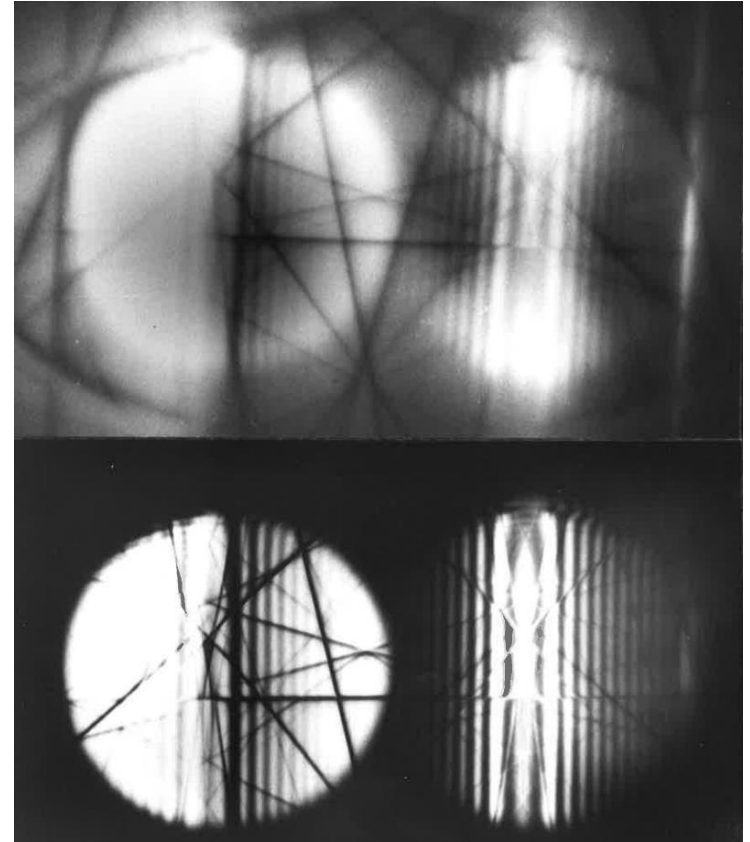
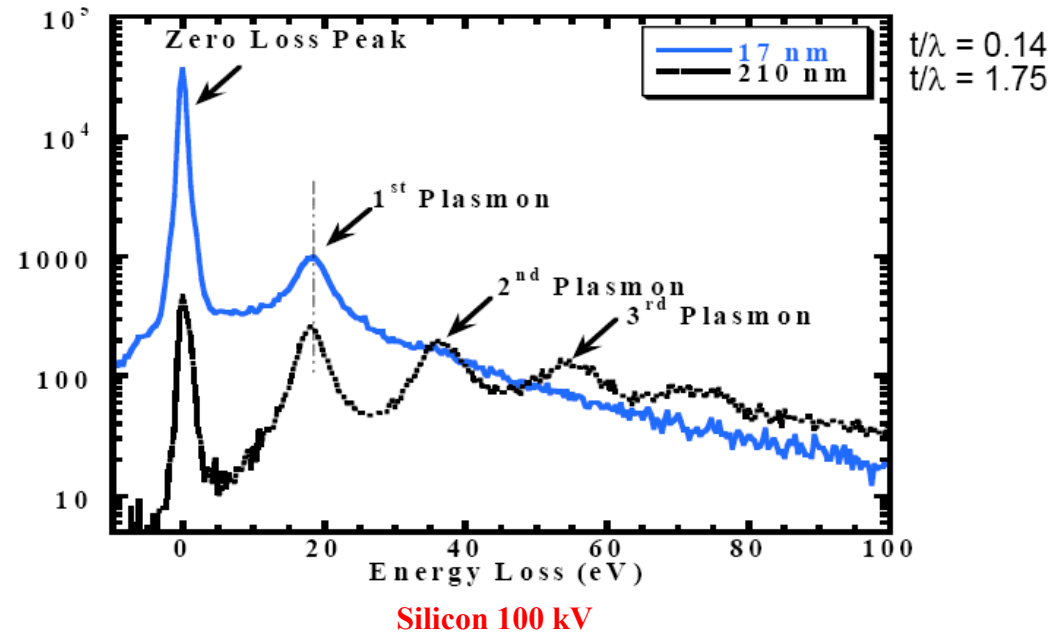


Covered Topics

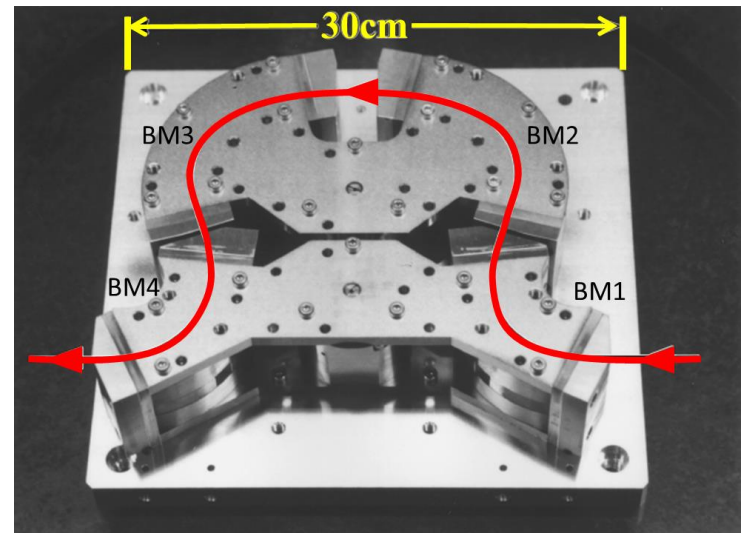
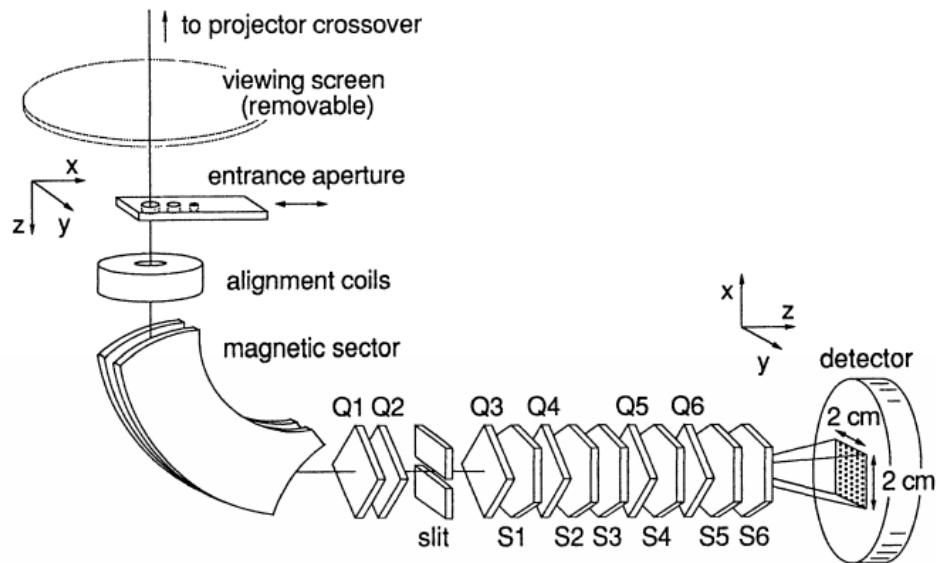
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Energy Filtering

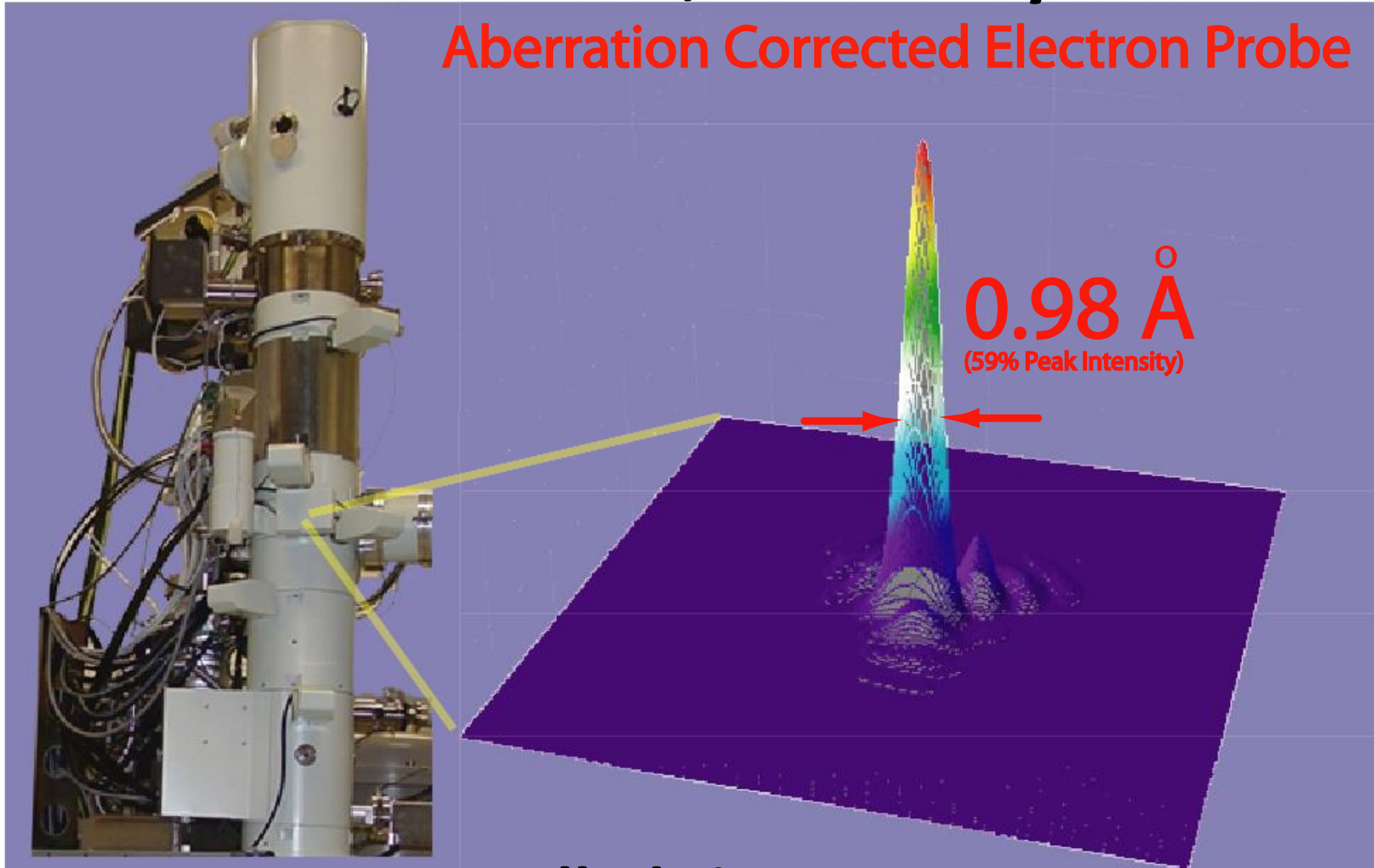


Top: Unfiltered
Bottom: Filtered



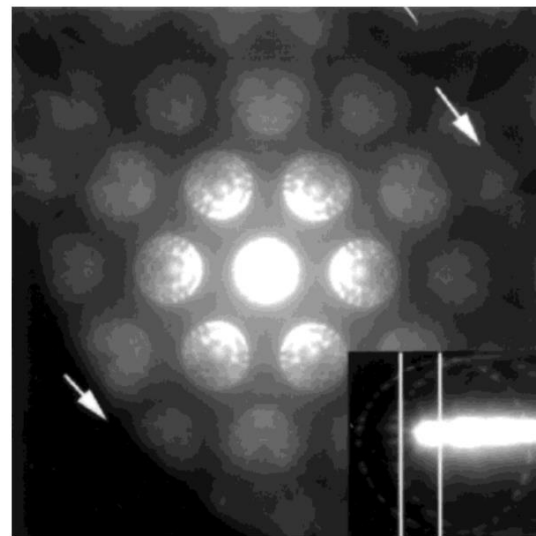
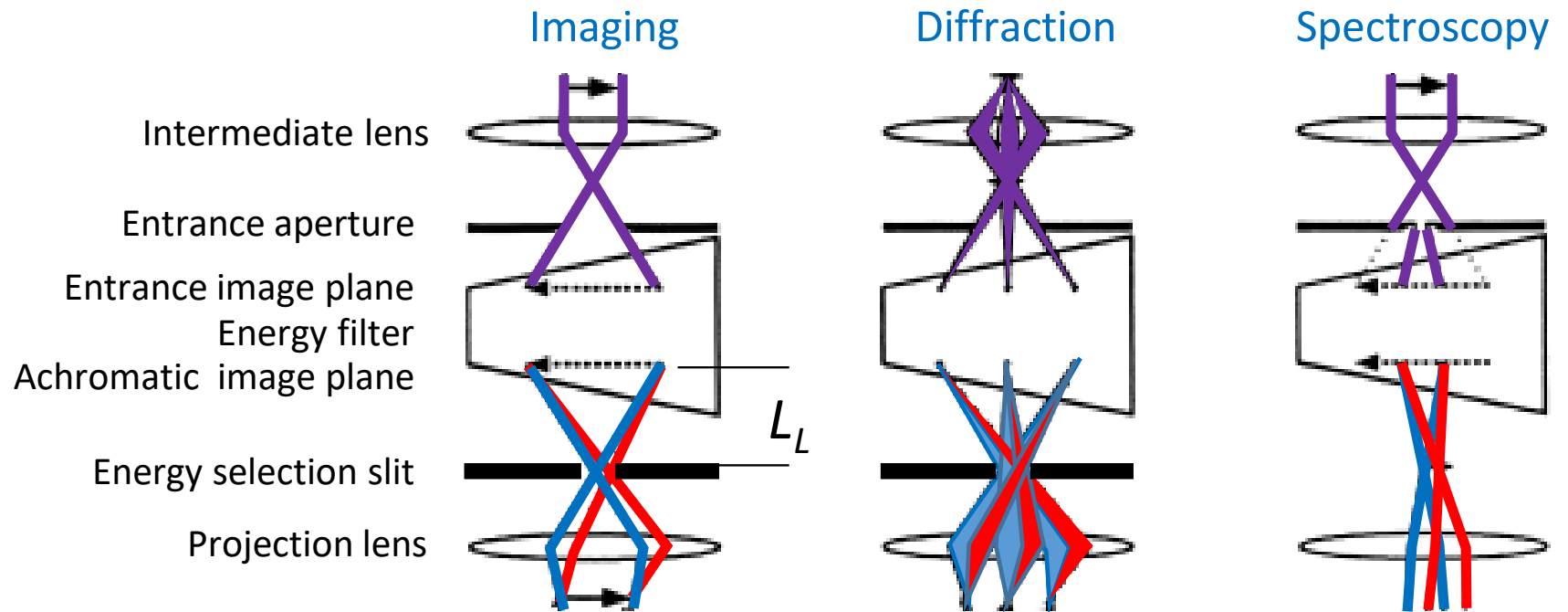
JEOL 2200FS @ CMM, University of Illinois

Aberration Corrected Electron Probe

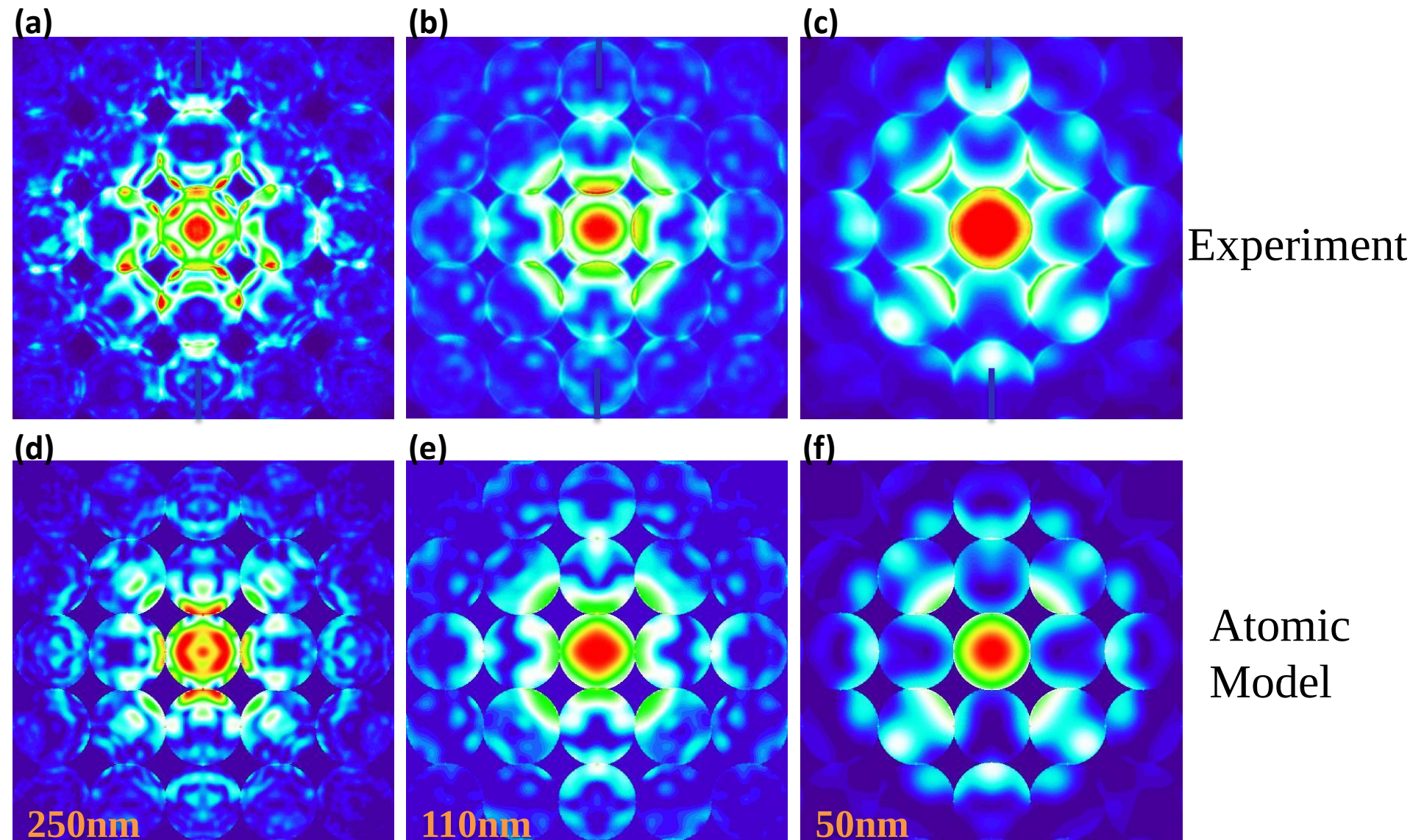


Installed since 2008





Energy-Filtered CBED of Ferroelectric BaTiO₃



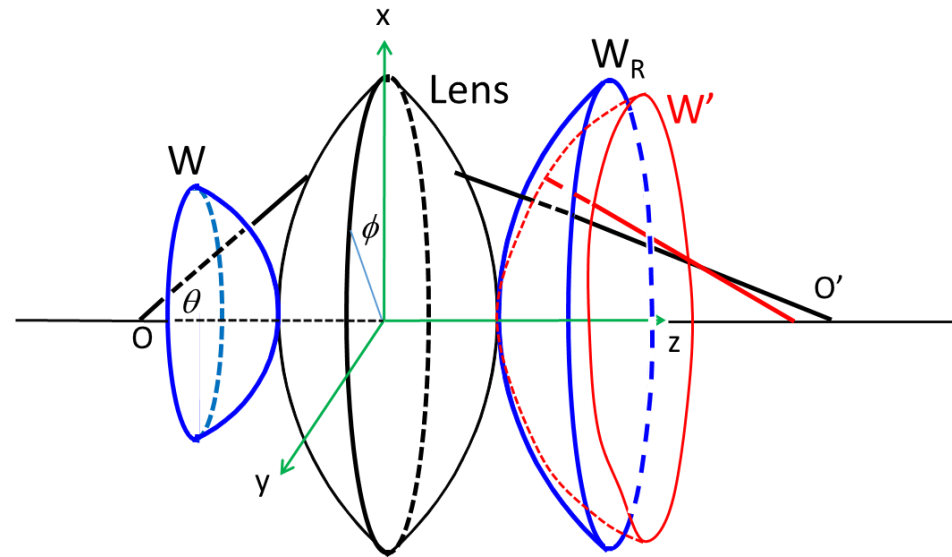
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JEOL 2200FS @ CMM, University of Illinois

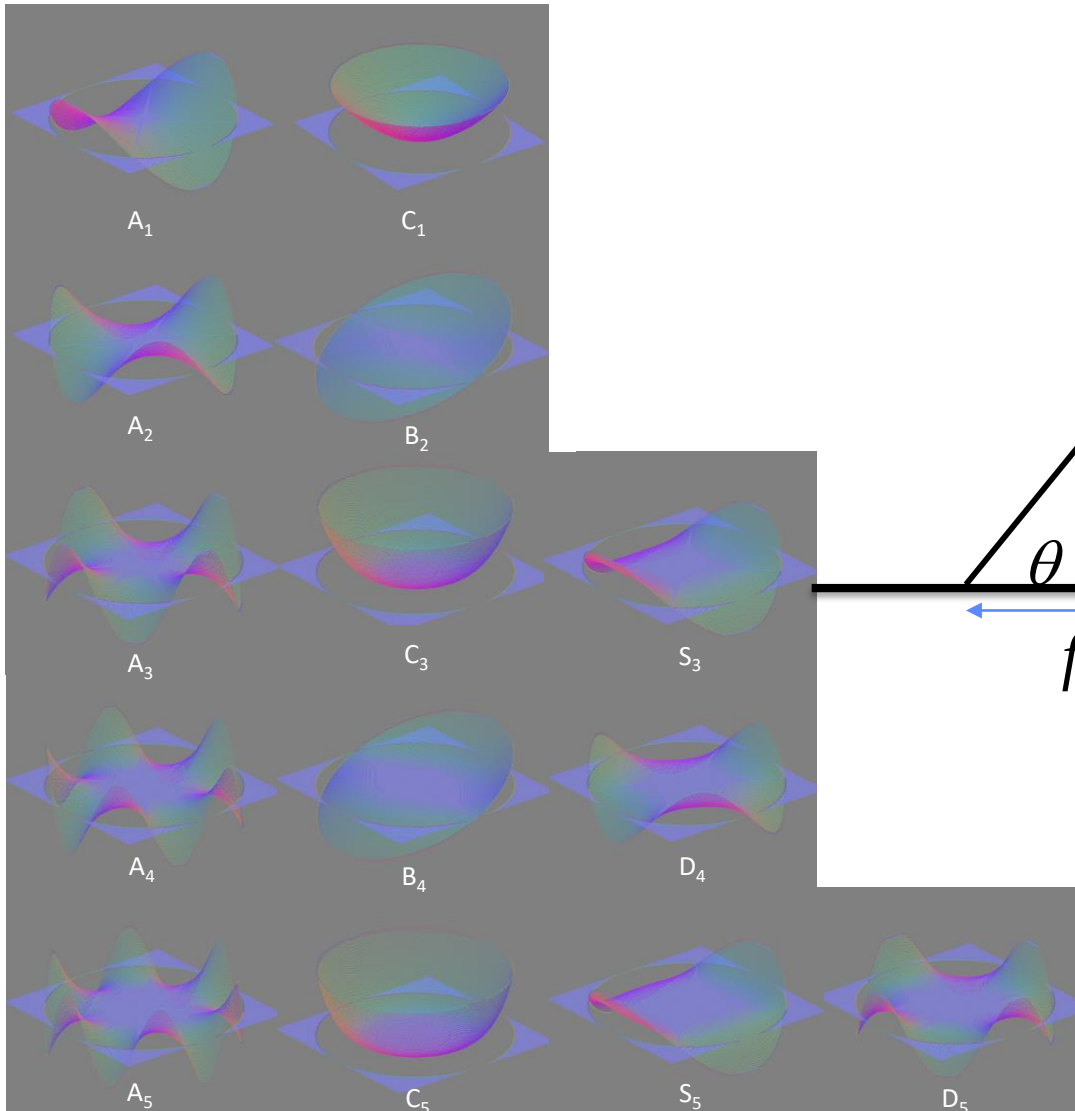
Aberration Corrected Electron Probe



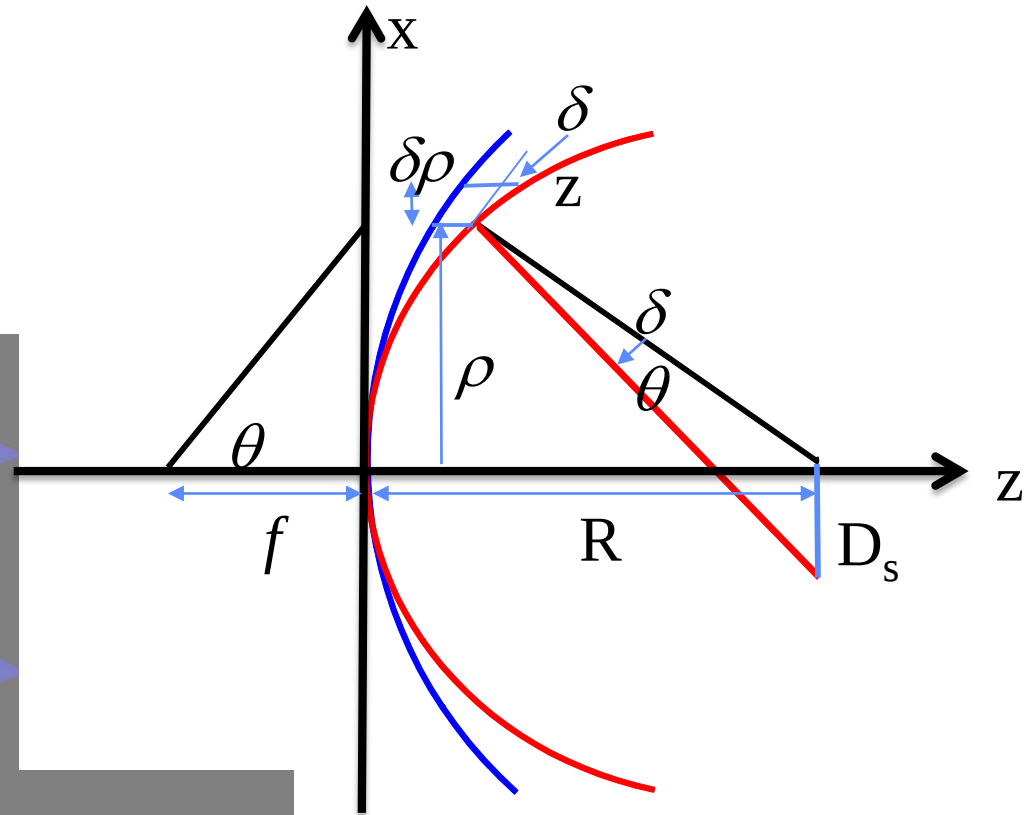
$$\chi(\omega, E) = \frac{2\pi}{\lambda} \text{Re} \left\{ \frac{1}{2} \varpi^2 A_1 + \frac{1}{2} \omega \varpi C_1 + \frac{1}{3} \varpi^3 A_2 + \omega^2 \varpi B_2 + \frac{1}{4} \varpi^4 A_3 + \frac{1}{4} (\omega \varpi)^2 C_3 + \omega^3 \varpi S_3 \right. \\ \left. + \frac{1}{5} \varpi^5 A_4 + \omega^3 \varpi B_4 + \omega^4 \varpi D_4 + \frac{1}{6} \varpi^6 A_5 + \frac{1}{6} (\omega \varpi)^3 C_5 + \dots \right\}$$

Aberrations = Phase

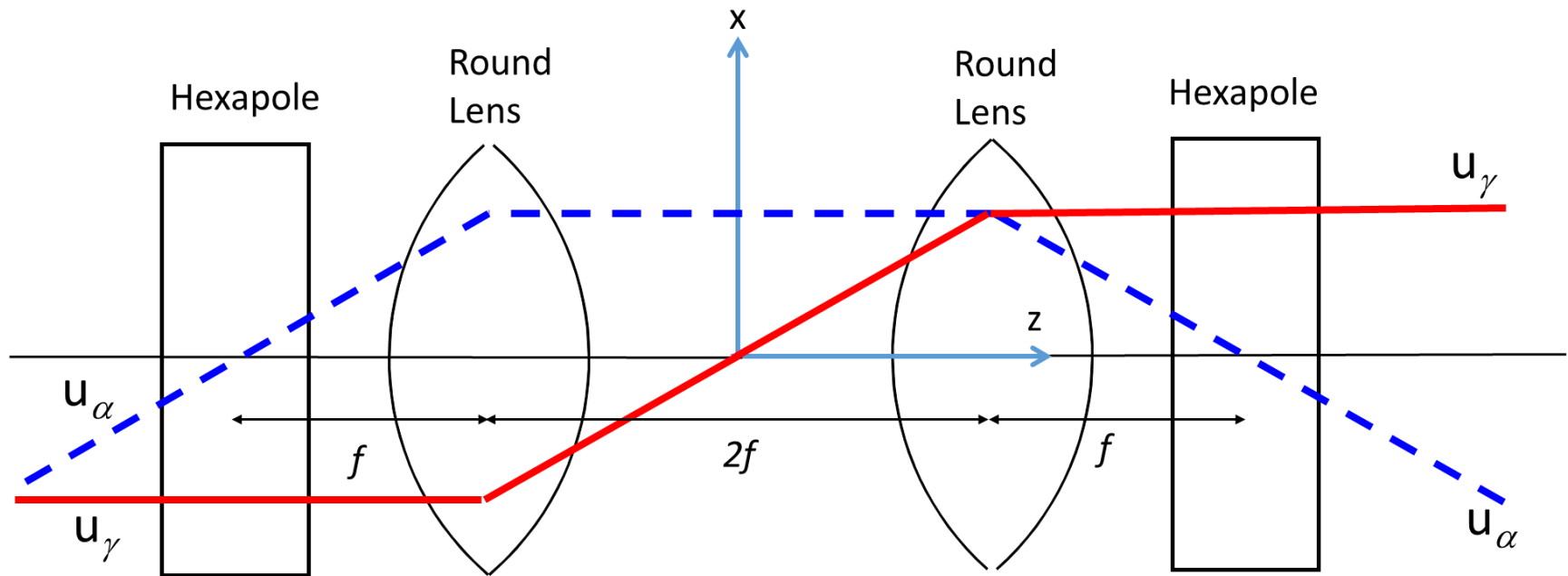
Aberration Coefficients



$$\chi(\theta) = 2\pi(C_s \theta^4 / 4) / \lambda$$

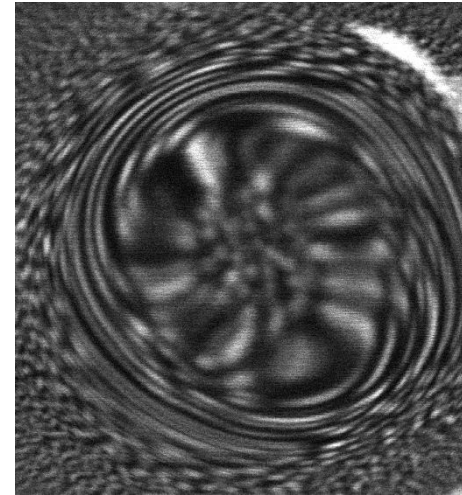
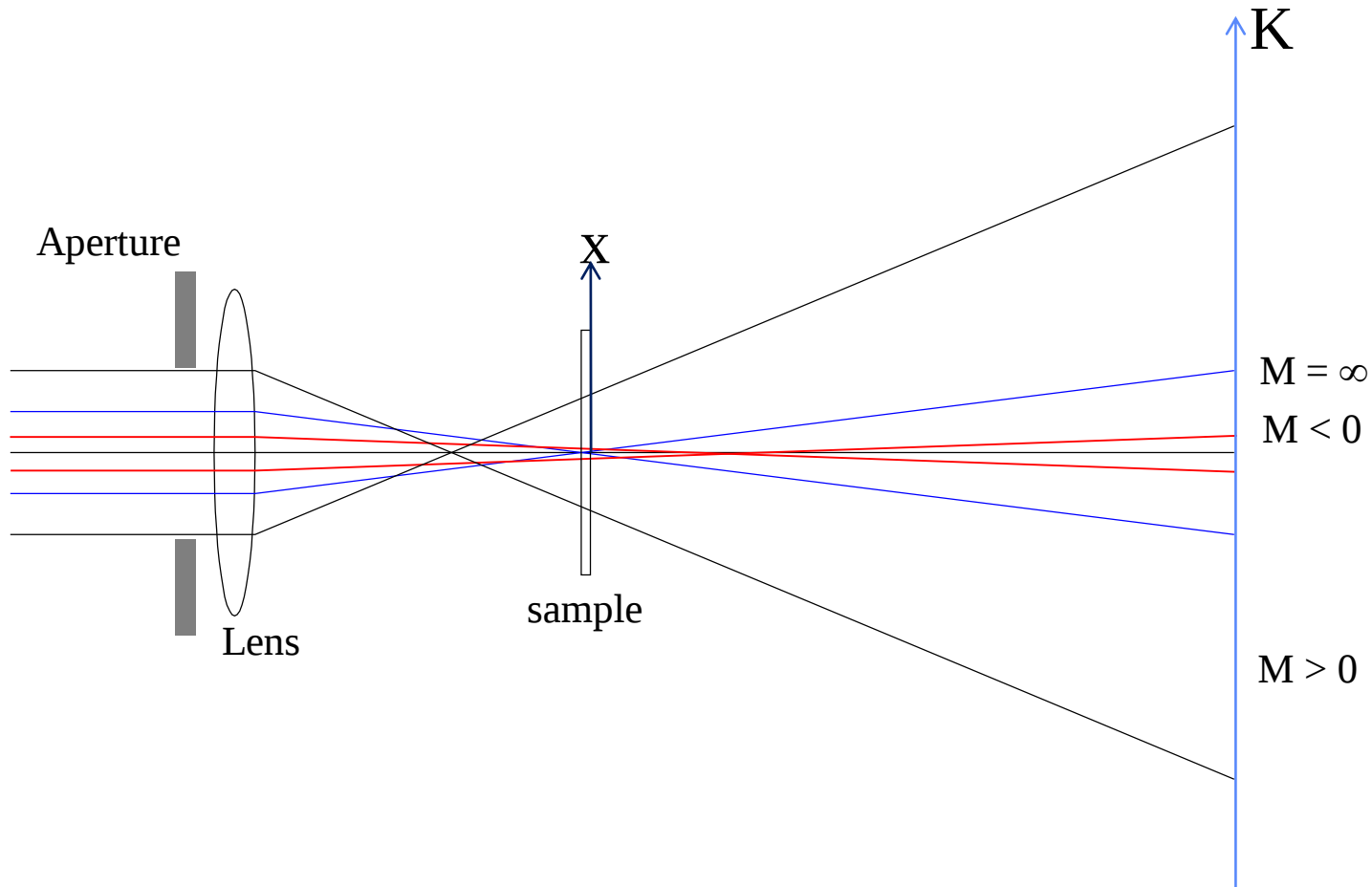


Aberration Corrector



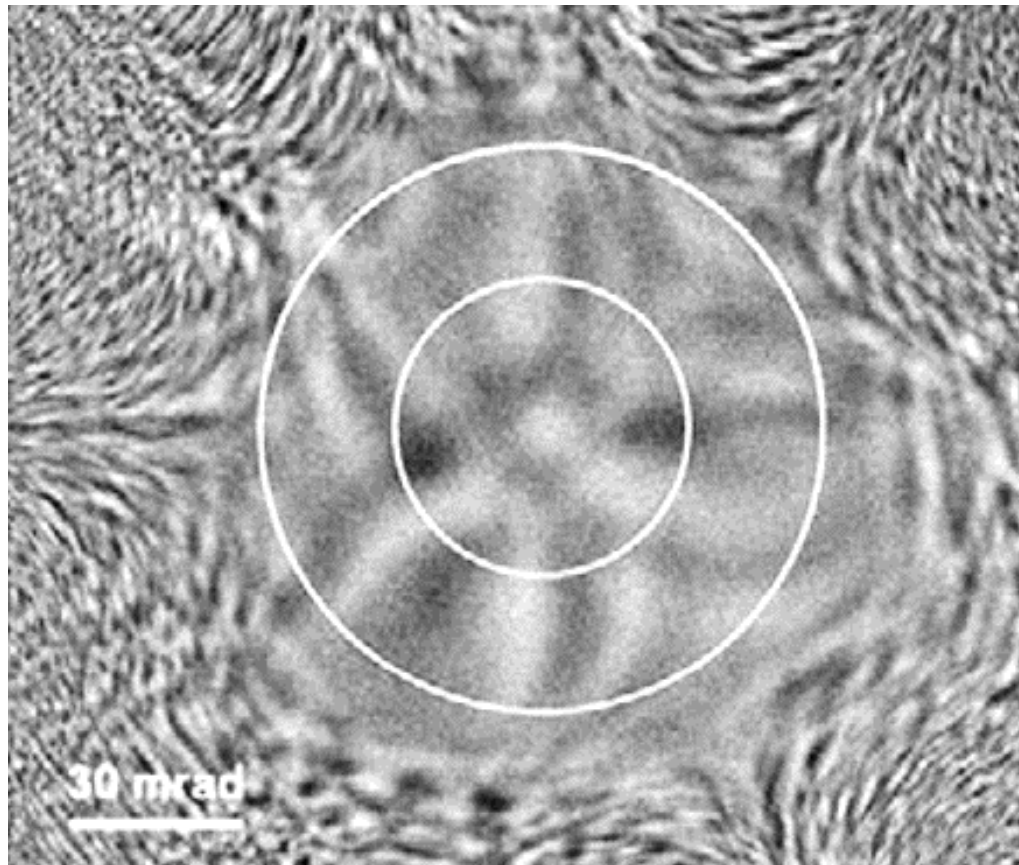
$$C_S = -3|\eta\Psi_{3s}|^2 f^4 L^3 < 0$$

Ronchigram

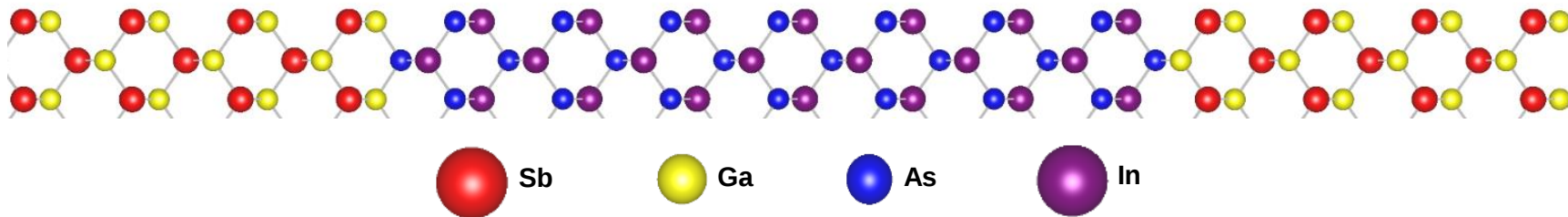
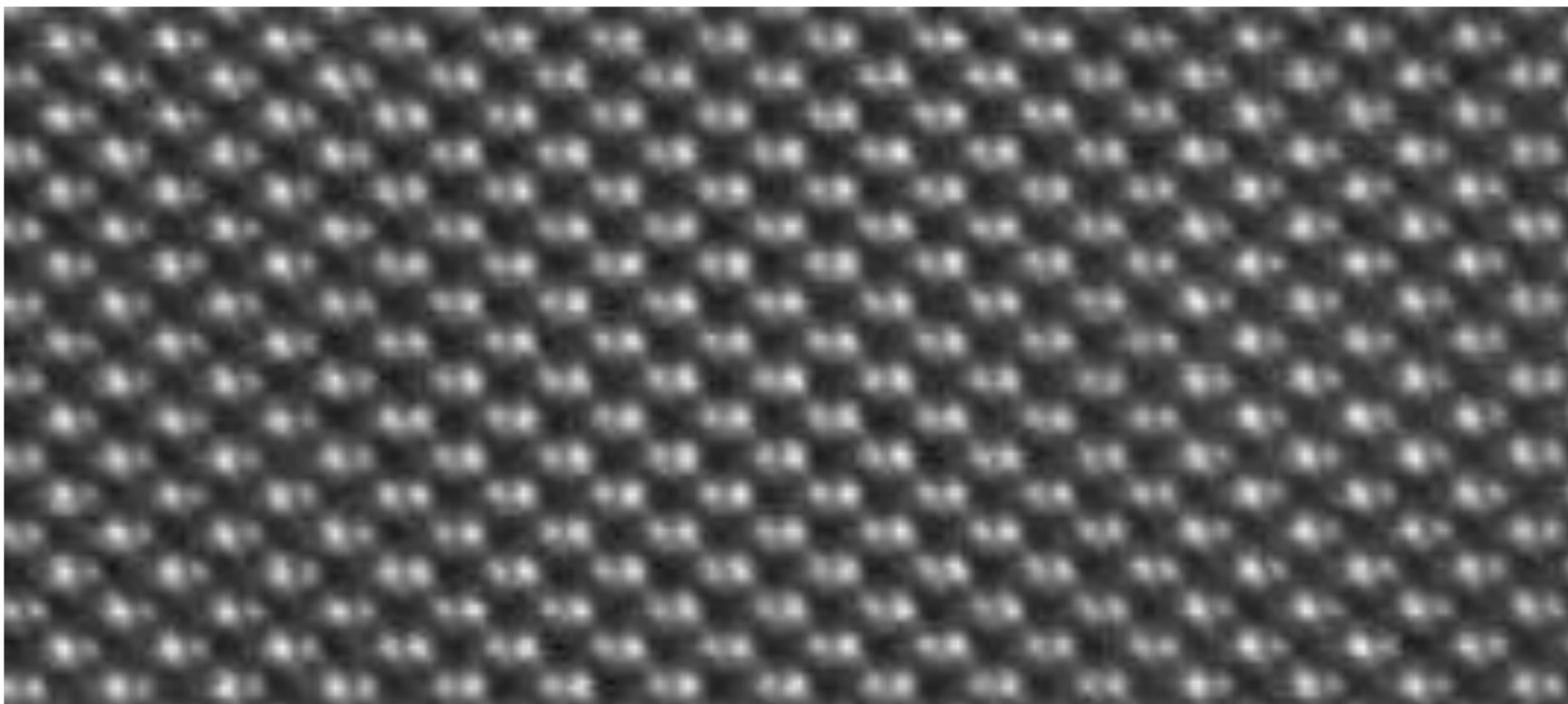


Higgs & Krivanek,
EMSA 1981

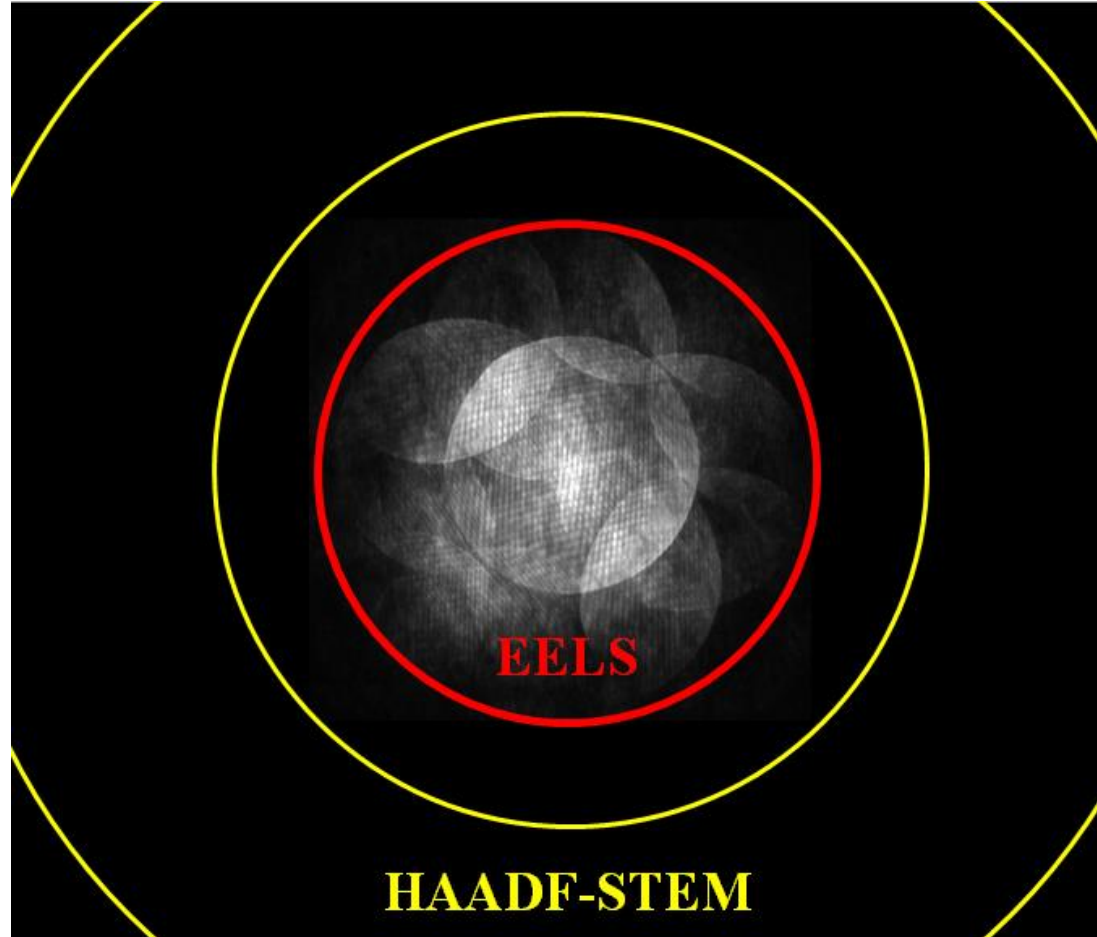
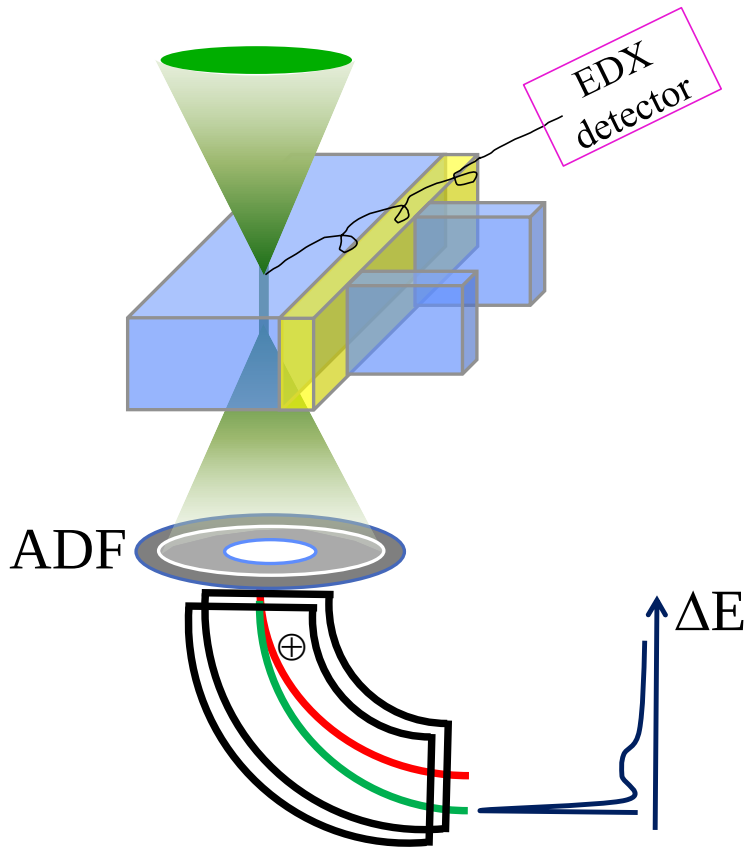
Ronchigram



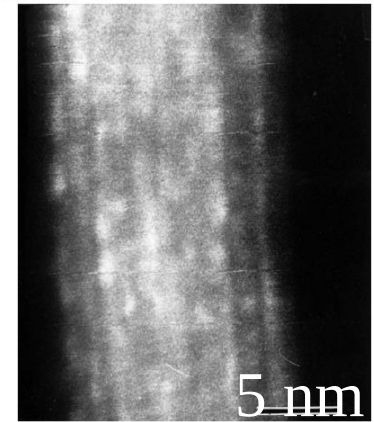
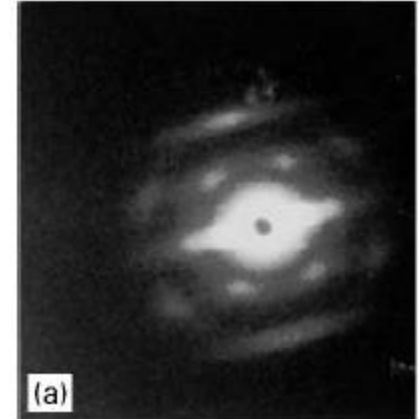
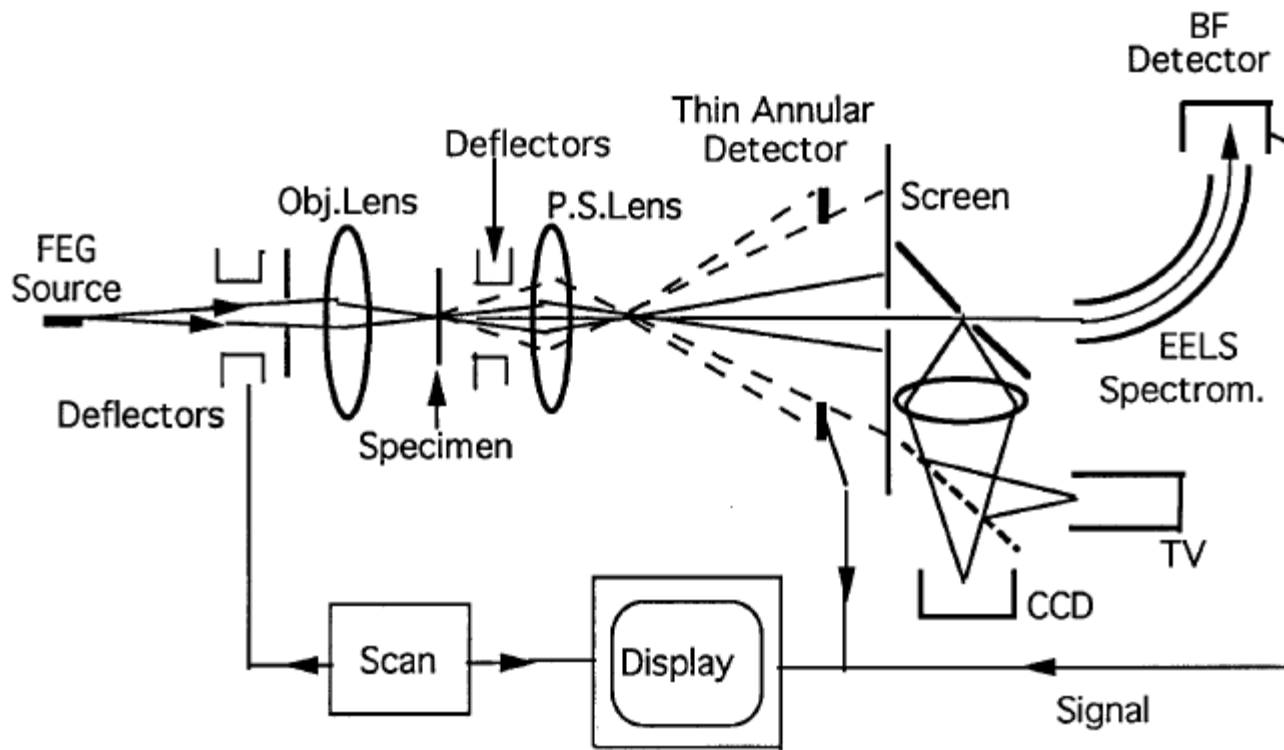
From JEOL2200F



STEM



Electron Nanodiffraction (END) in STEM

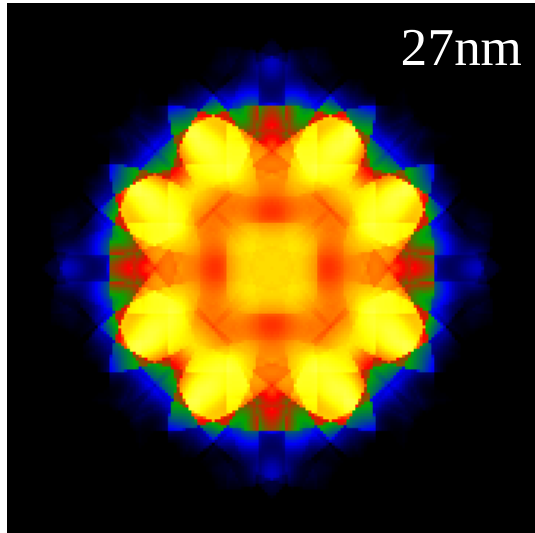


**Probe focused to 0.7 nm at the specimen level;
Nanodiffraction patterns recorded from: 1) any
spot, 2) A scan line, or 3) over a small scan area.**

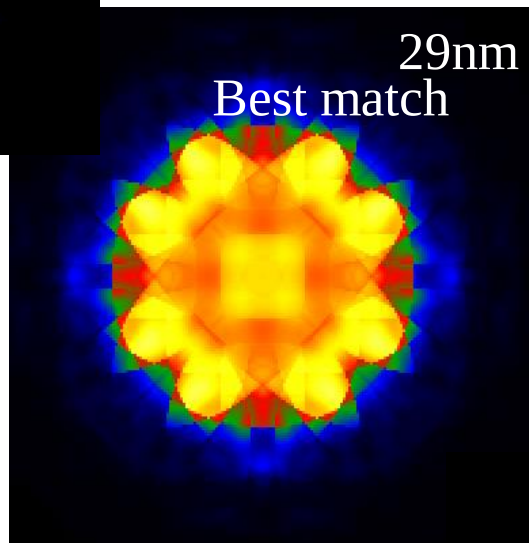
John Cowley, Ultramicroscopy 68 (1997) 1-12

Position Averaged CBED

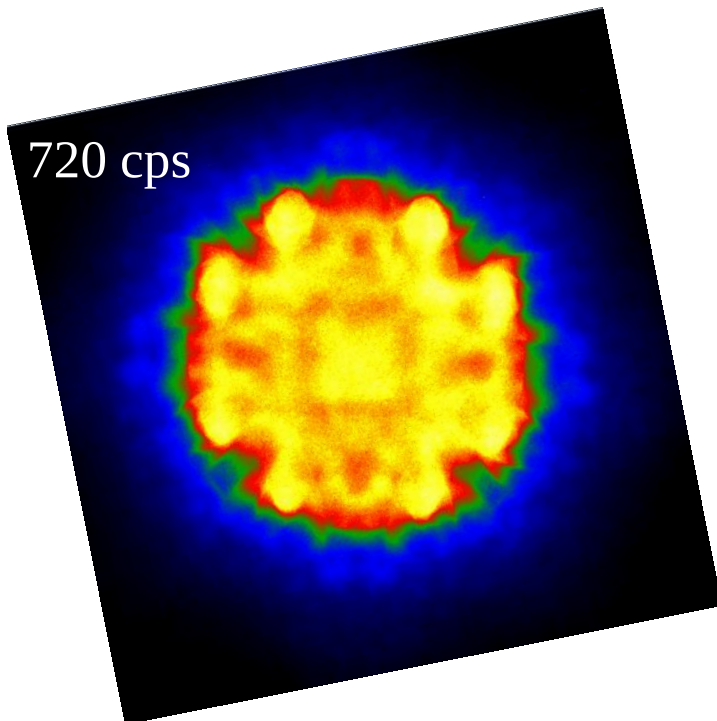
27nm



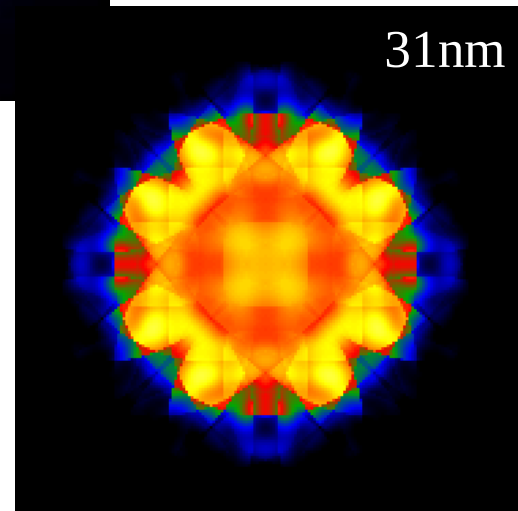
29nm
Best match



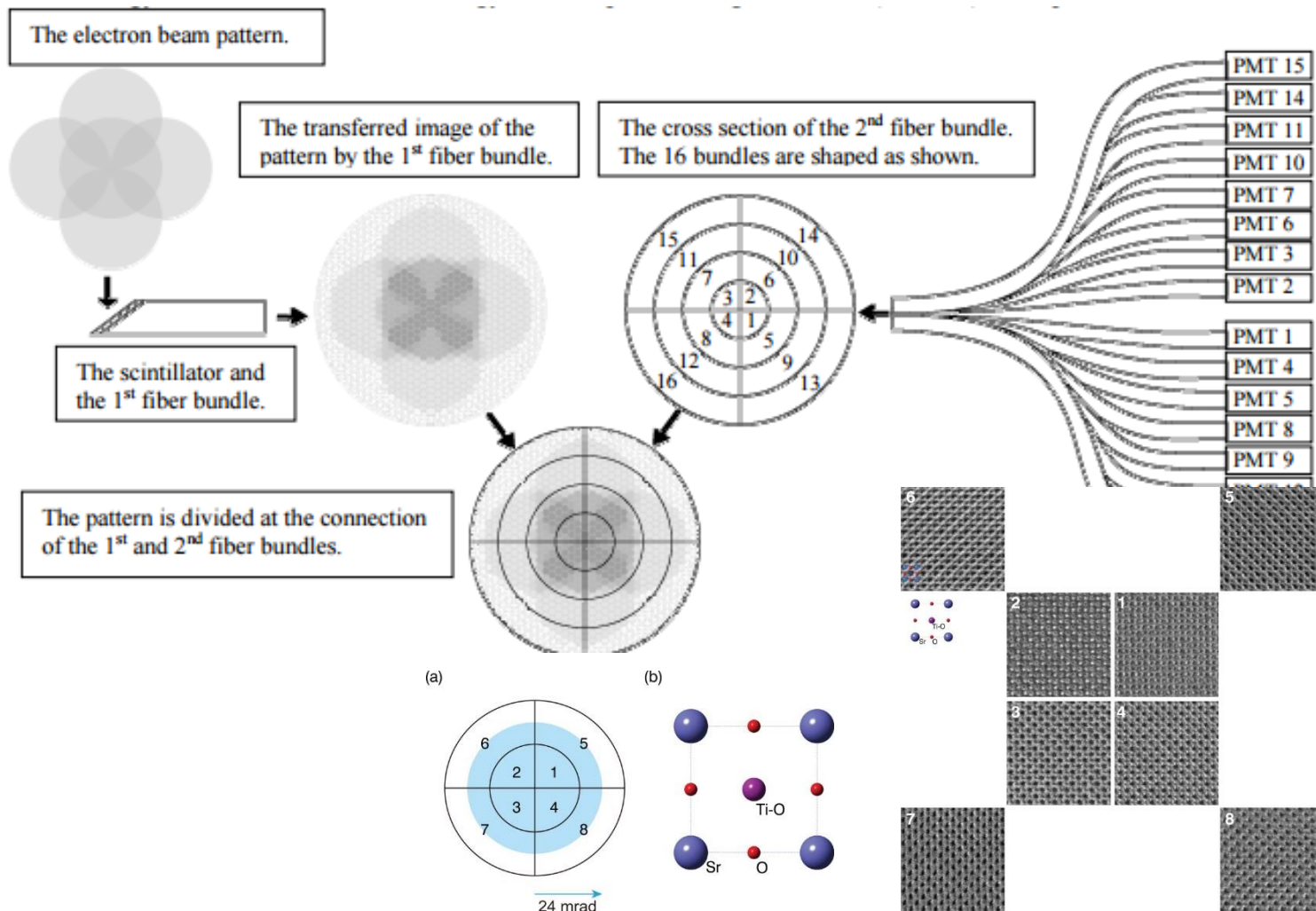
720 cps



31nm

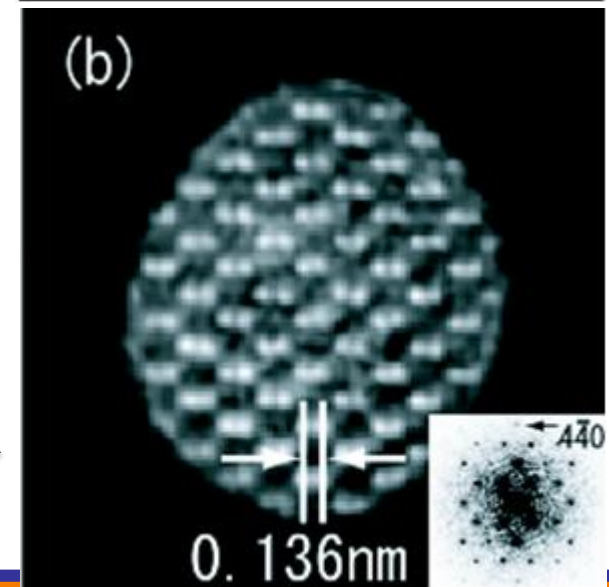
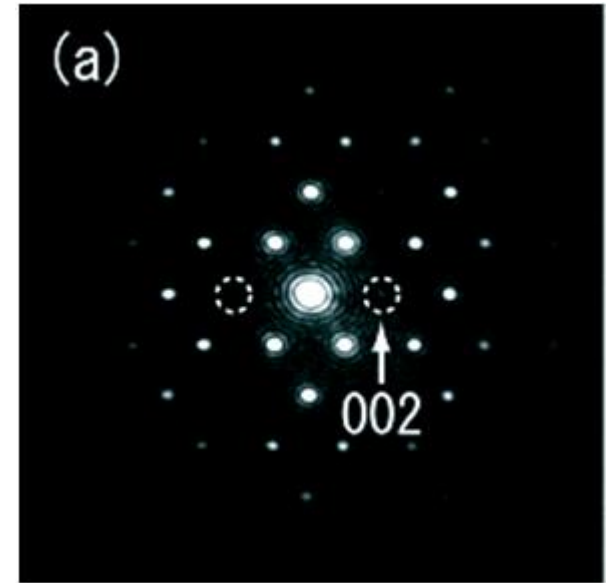
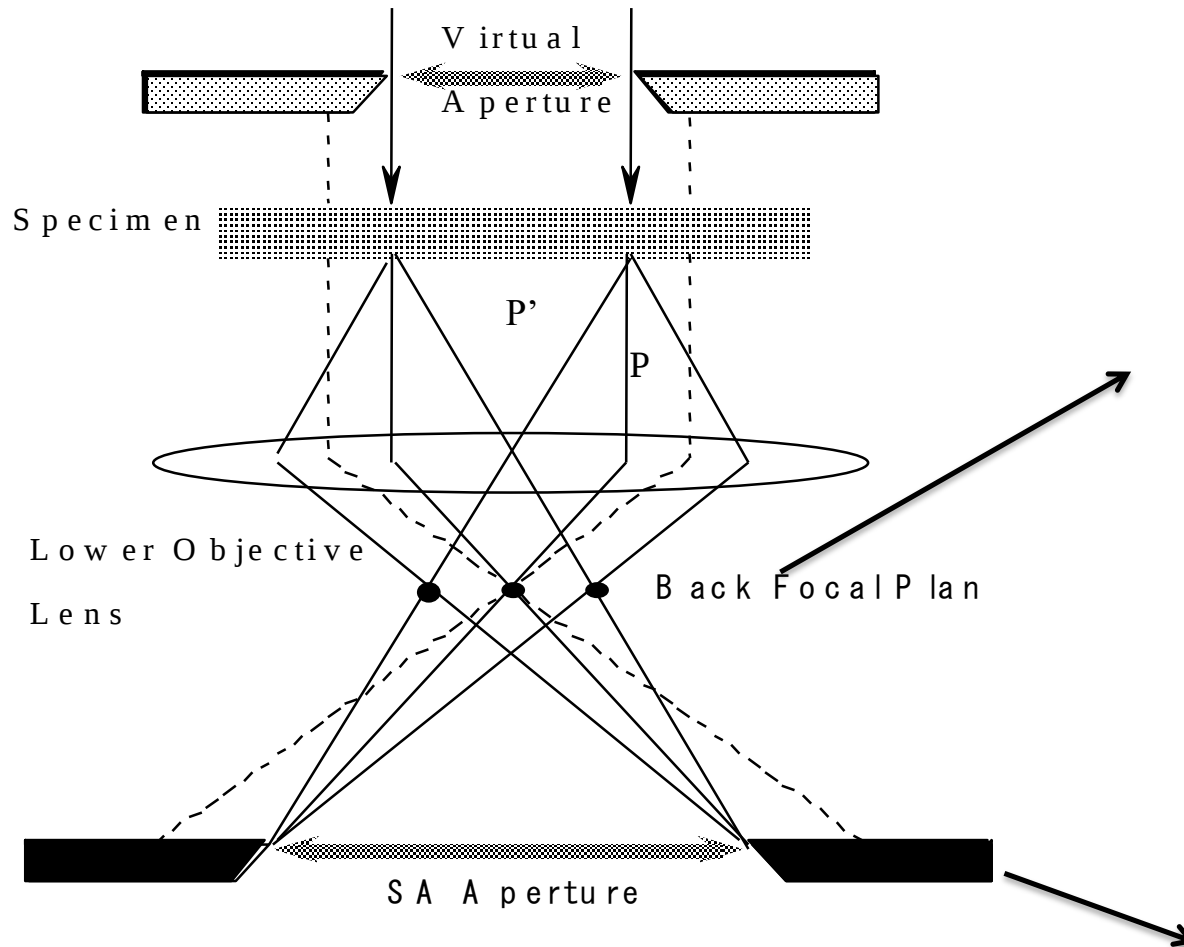


Segmented Detector



Kohno et al., Microsc. Microanal. 16 (Suppl 2), 2010

Selected Area Electron Diffraction with Cs Correction



Covered Topics

- **Electron diffraction techniques**
 - **Selected area electron diffraction**
 - **Convergent beam electron diffraction**
 - **Large angle methods**
 - **Precession electron diffraction**
 - **Nanoarea electron diffraction**
 - **Scanning electron nanodiffraction**
- **Energy-filtering**
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 - **Probe size**
 - **Coherence**
- **Electron detectors and radiation effects**



Beam Current

- Source brightness: The emission current density J per unit solid angle, $\beta_s = J/\pi\alpha^2$.
- The brightness β_s of a source is conserved and constant even if aberrations and aperture stops are permitted.
- The beam current after the condenser aperture is given by

$$I_b = \beta_s \pi^2 \alpha_c^2 (d_s / 2)^2$$

*The probe radius plotted
against the probe
convergence angle for
brightness $10^{12} \text{ A/m}^2/\text{sr}$*

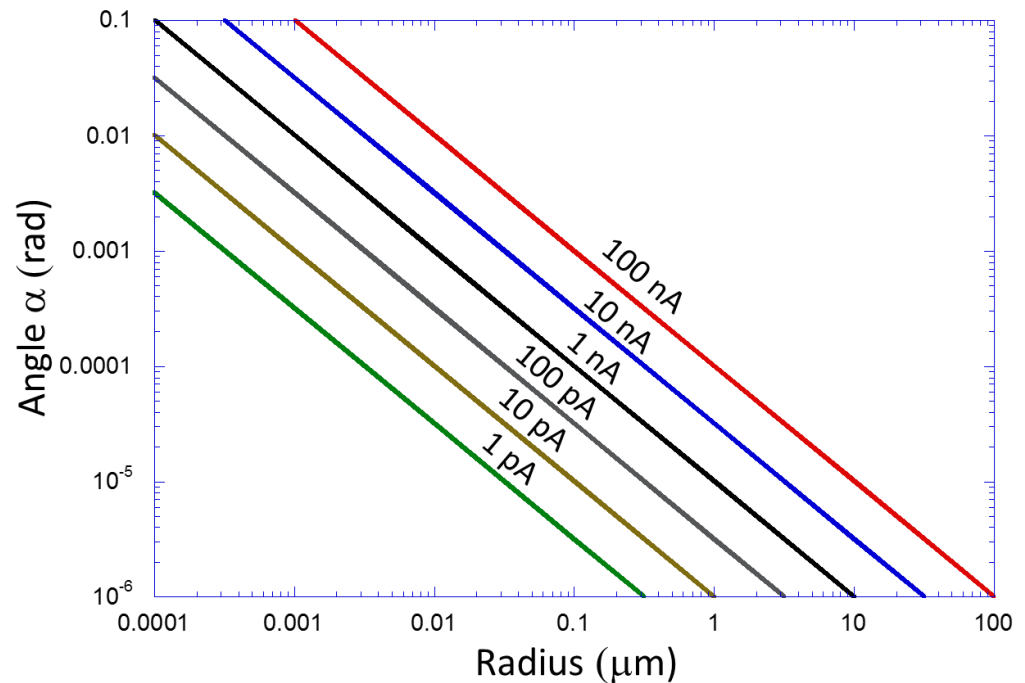


Table 1. Probe Conditions 1 and 2 Used for High Spatial Resolution STEM Imaging*

Conditions	1 HR-STEM	2 HR-STEM	3 STEM EELS	4 STEM HR-EELS
Emission current (μA)	160	160	160	80
Energy resolution (eV)	0.8	0.8	0.9	0.6
CL aperture	30 (μm)	20 (μm)	30 (μm)	40 (μm)
	26.5 (mrad)	17 (mrad)	26.5 (mrad)	34.5 (mrad)
Probe size setting	8	8	3	1
Probe current (pA)	30	13	160	120
Spatial resolution (nm) ^a	<0.078	<0.096	0.11	0.13

*Probe condition 3 for STEM imaging and EELS, and 4 STEM and high-resolution EELS. The energy resolution is measured using FWHM of ZLP using half collection angle (17 mrad).

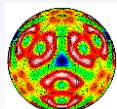
^aThe spatial resolution is measured using FFT of Si along [110].

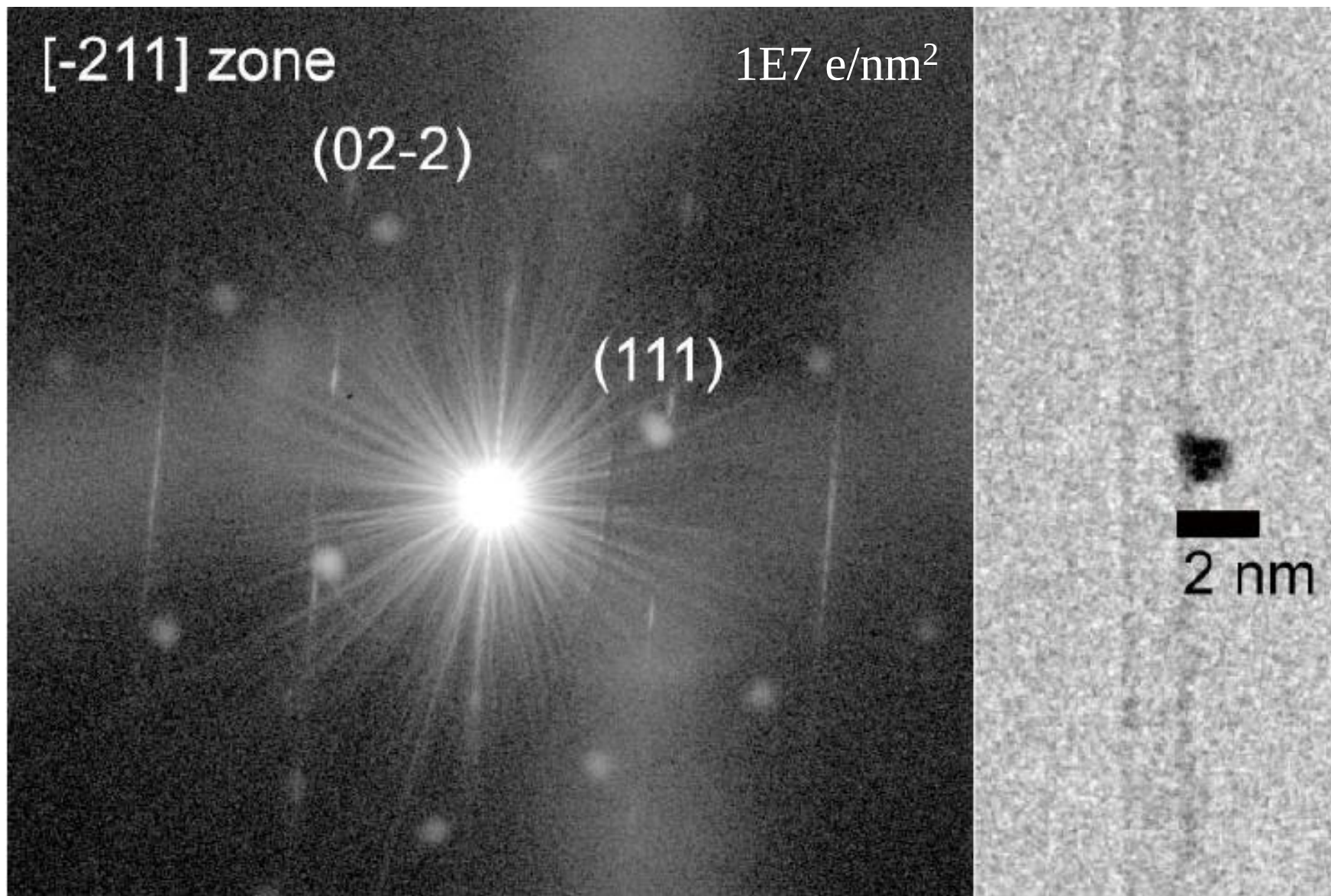
In STEM, for a 30 pA probe

$$30 \times 10^{-12} / 1.6 \times 10^{-19} \times 10 \times 10^{-6} \times 25 \leftarrow 5 \times 5 \text{ points}/\text{\AA}^2 \text{ sampling}$$

= 50k electrons

Recording time (s)

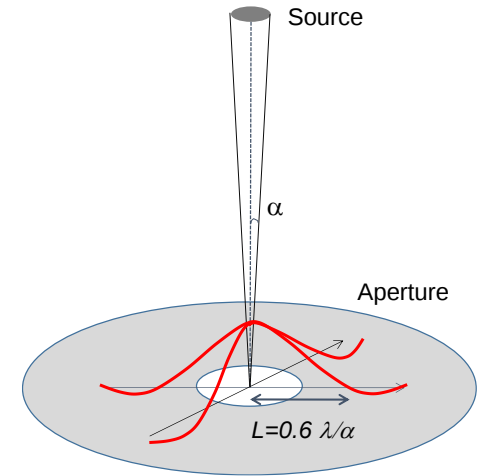
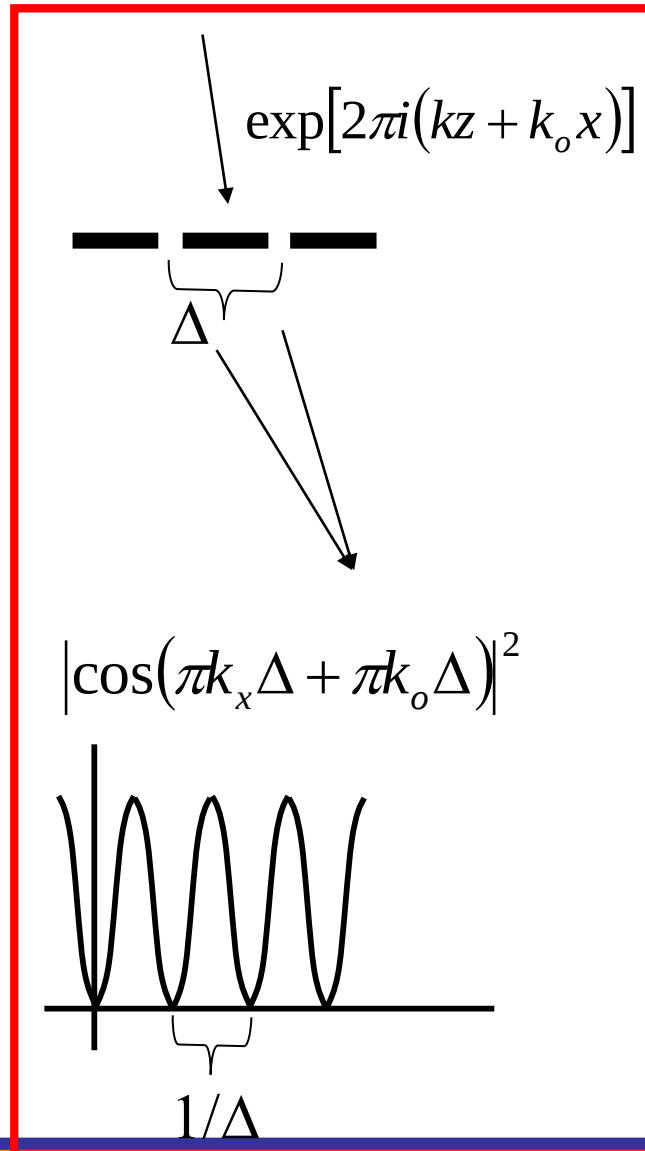
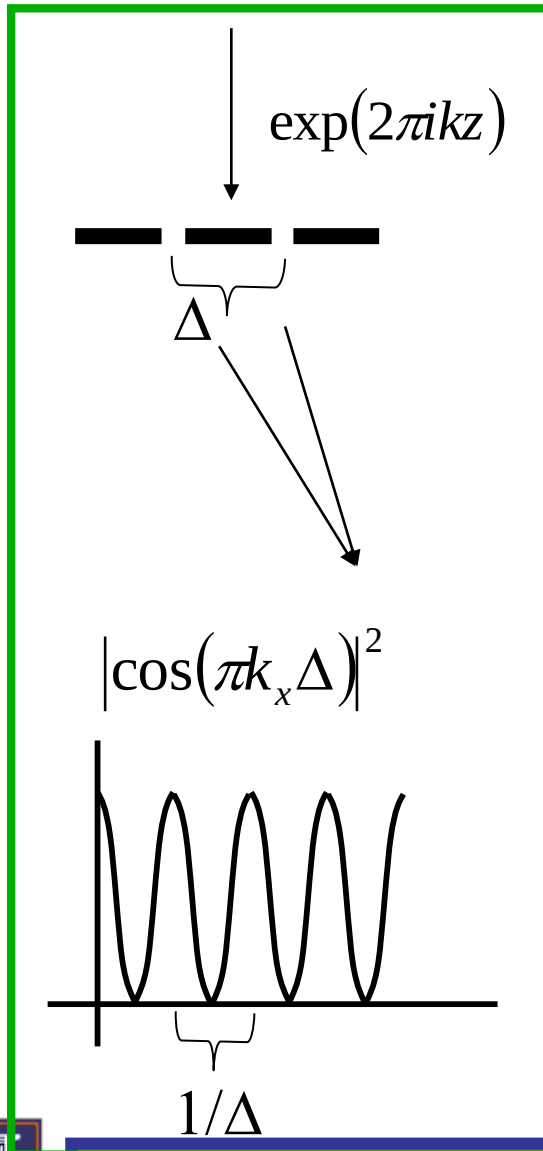




Weijie Huang, Ph.D. Thesis, UIUC



Coherence Length and Coherent Current

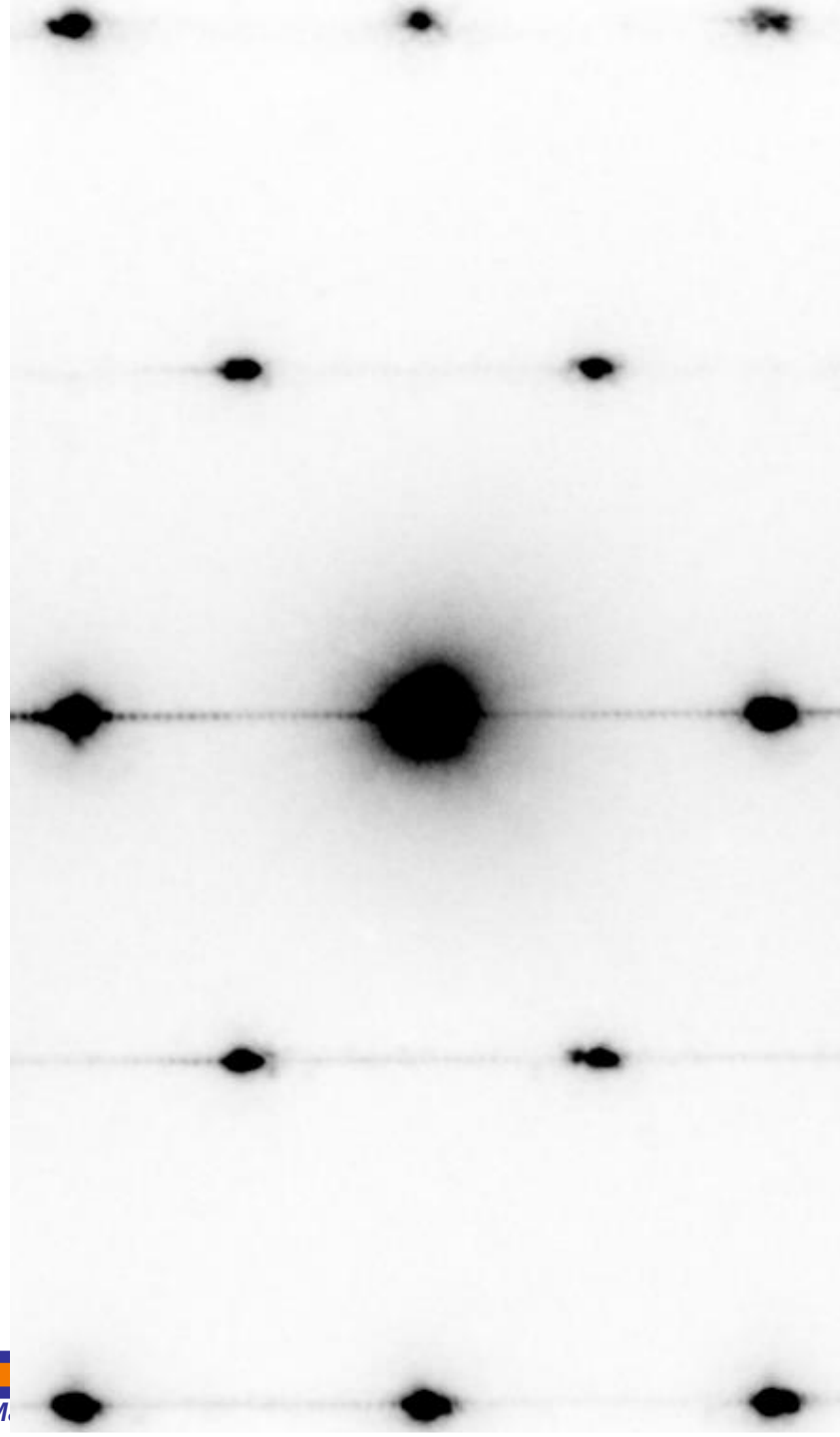
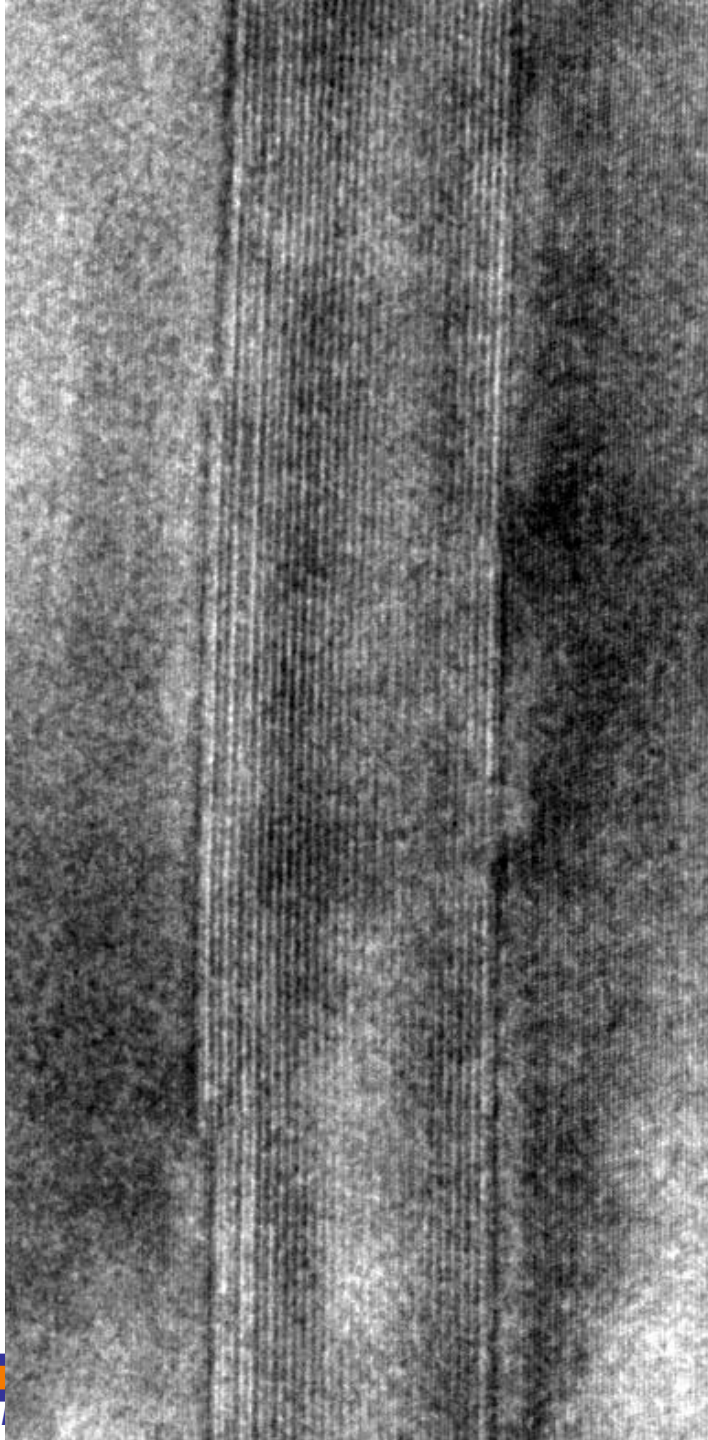


$$L = 0.6 \lambda / \alpha$$

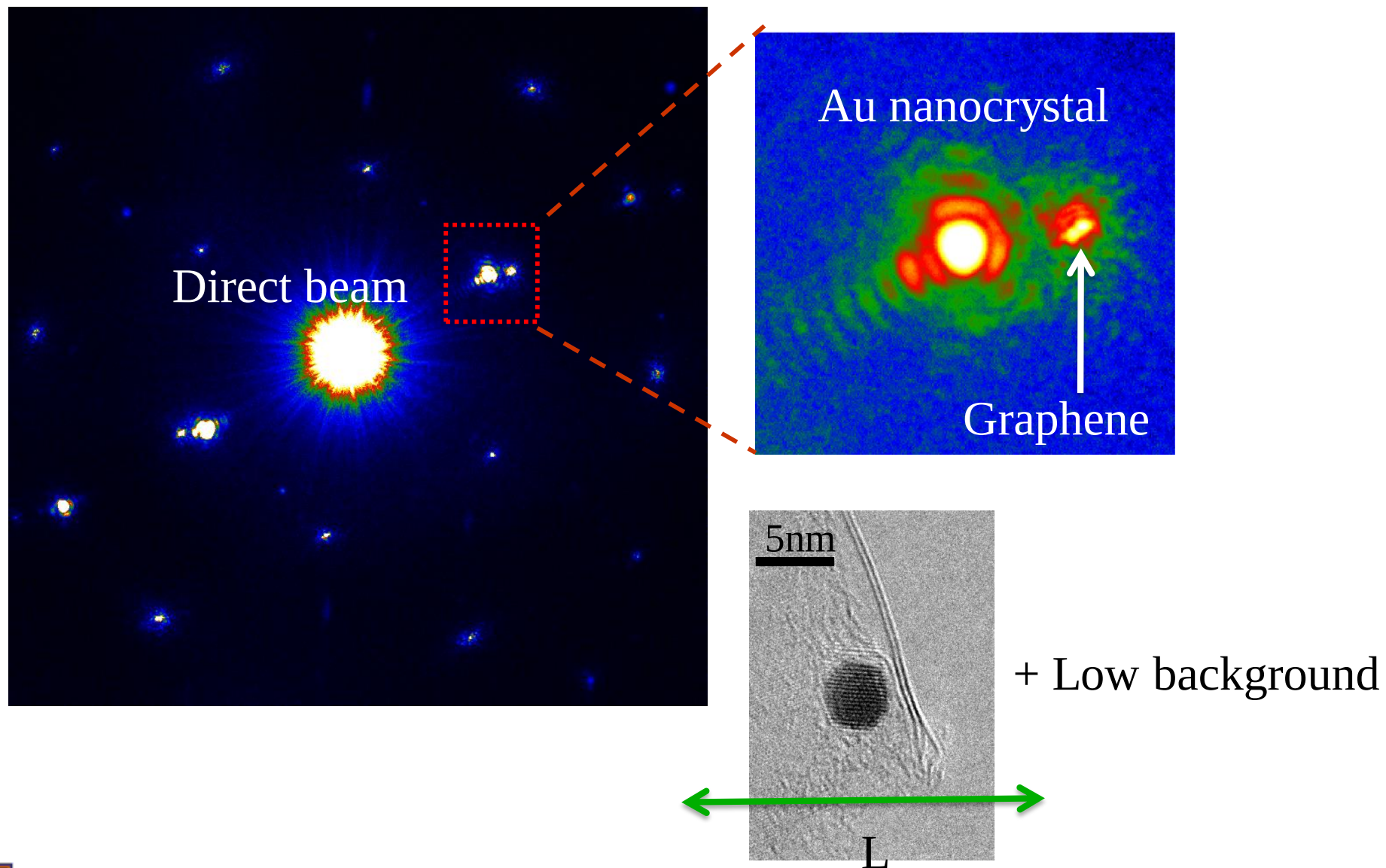
$$I_{coh}(\theta) = -\ln[\gamma(\theta, 0)] \beta_s \lambda^2$$

$$\gamma(\theta, 0) = \exp\left[-(\pi \theta r_s / \lambda)^2\right]$$

θ is the semi acceptance angle of the CA

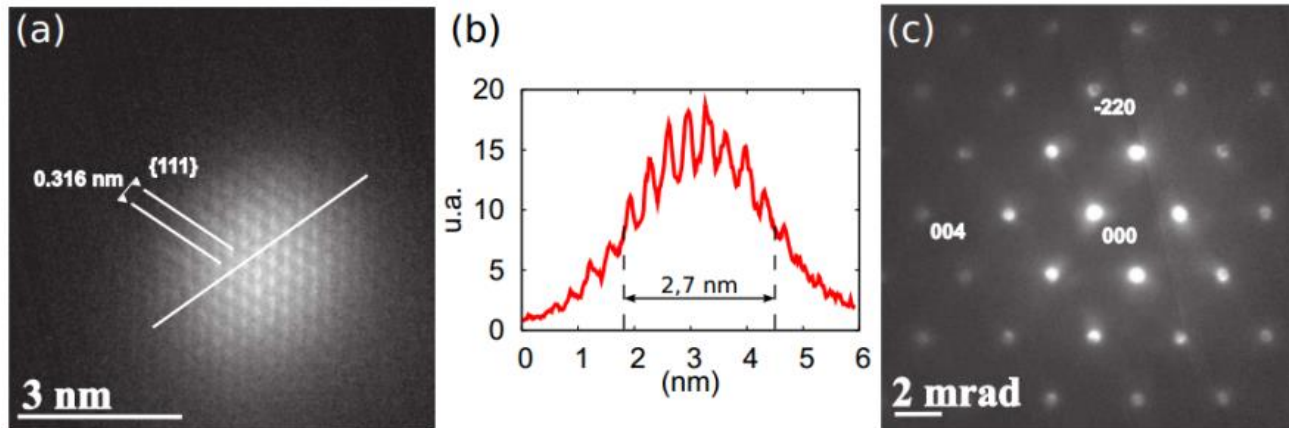


Coherent Electron Diffraction of Au Nanocrystal



Probe Size

Coherent and aberration free $d_{FWHM} = 0.52 \frac{\lambda}{\theta}$



Coherent with aberrations

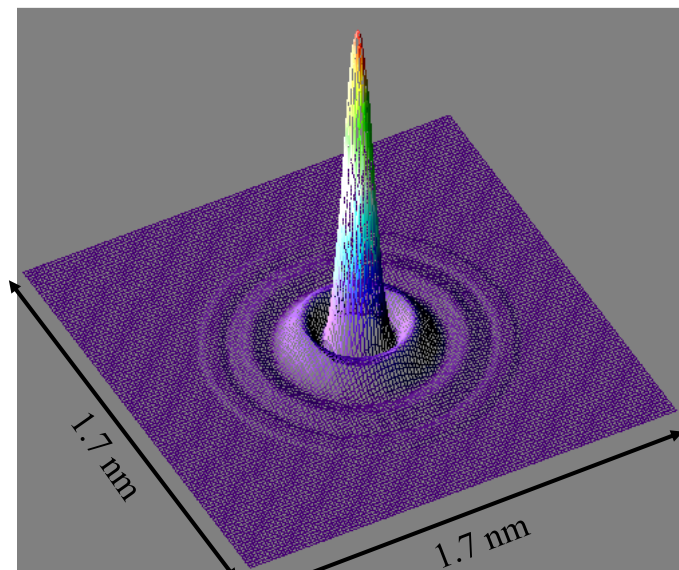
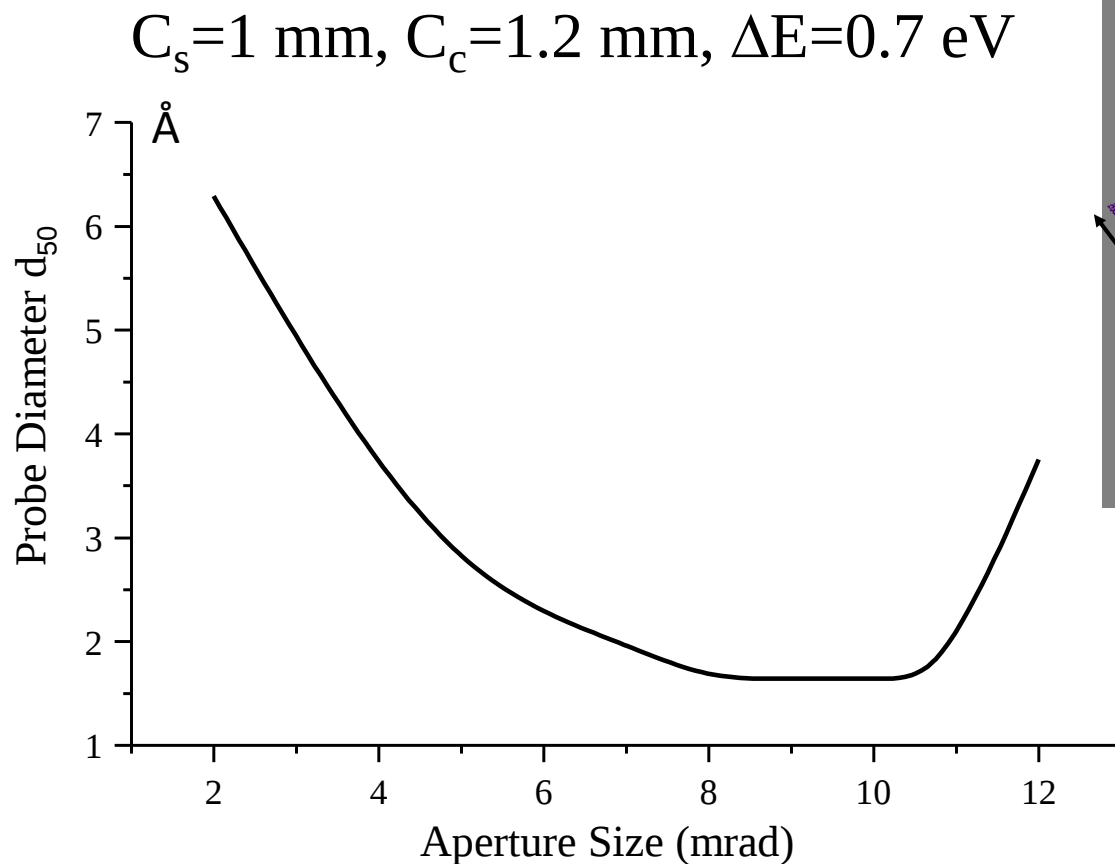
$$\phi_p(x, y) = FT \left(\frac{A\sqrt{\pi}}{a} \exp \left[-k_t^2 / (a / M\pi)^2 \right] A(\vec{k}_t) \exp \left[i\chi(\vec{k}_t) \right] \right)$$

Incoherent

$$d_o^2 = d_s^2 + d_d^2 + d_{sa}^2 + d_c^2 + d_f^2$$

Source image diameter, diffraction broadening, lens aberrations, Cc and focusing error

Electron Probe Formation



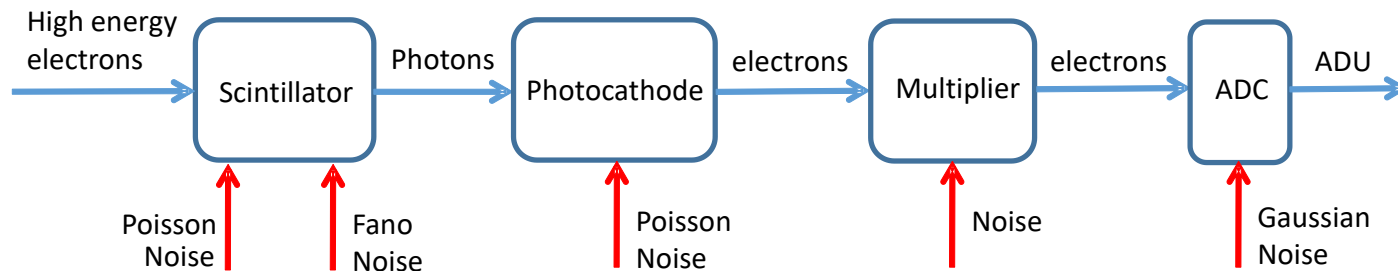
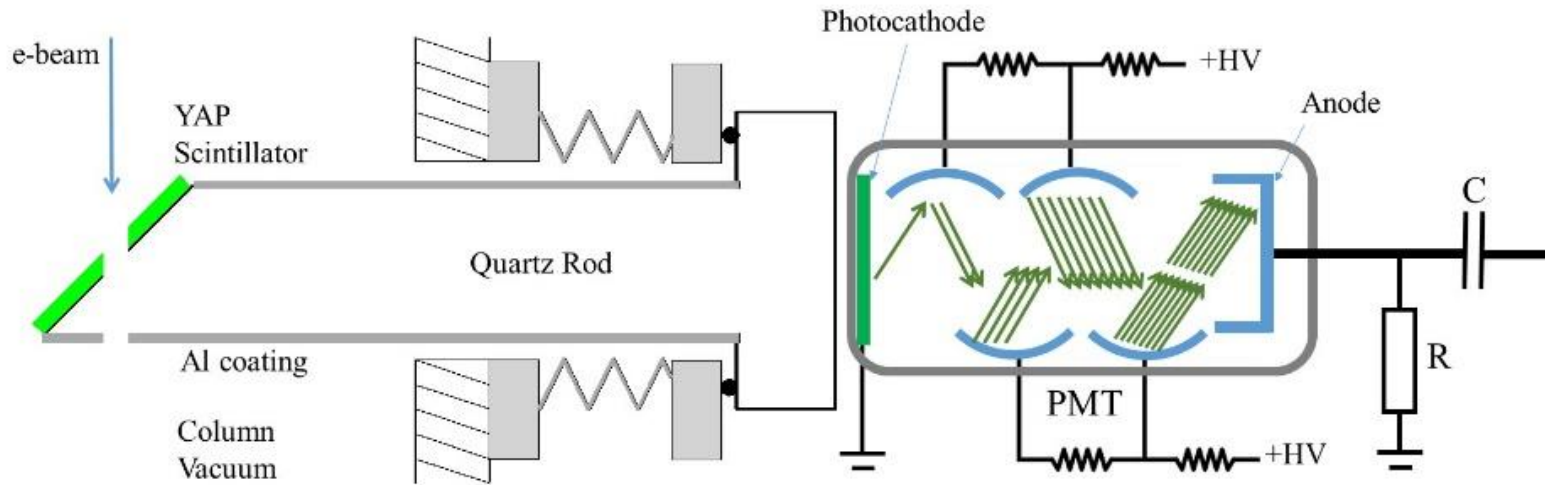
@Scherzer focus

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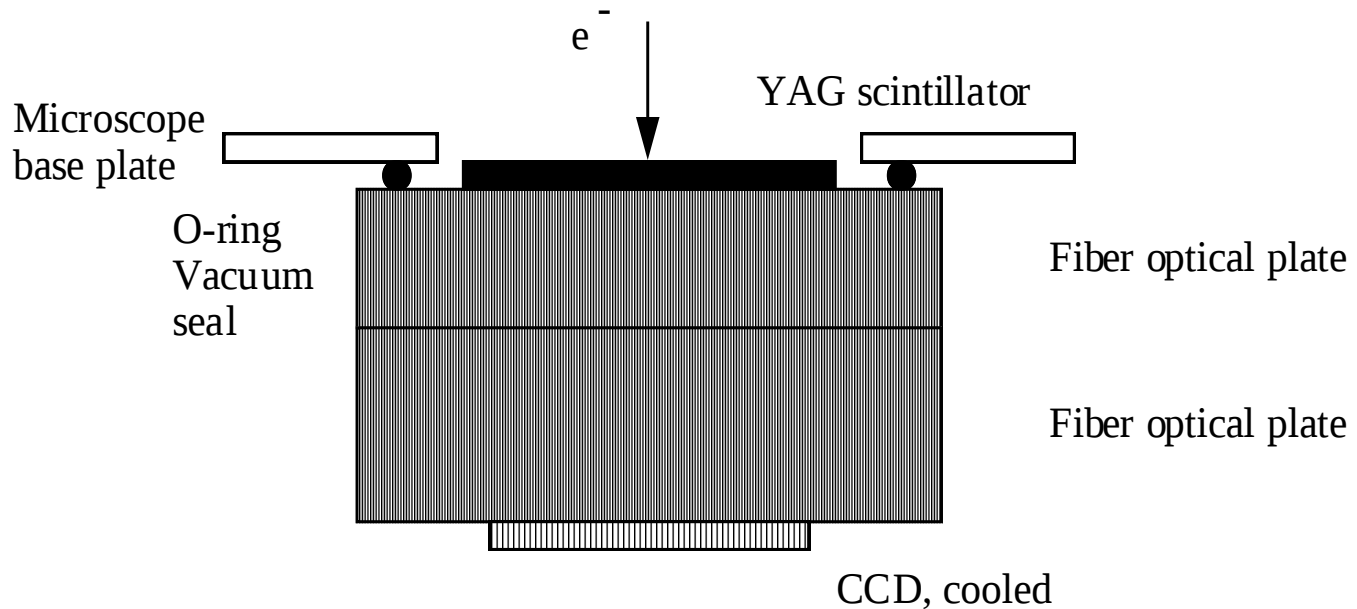


Electron Detection



$$DQE = \left(SNR_{out} / SNR_{in} \right)^2$$

Electron Recording: CCD cameras



Basics characteristics:

Number of pixels : 512x512, 1024x1024, 2048x2048, 4096x4096

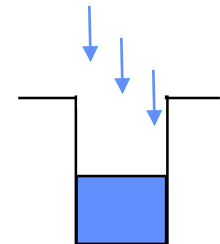
Pixel size : $\sim 24 \mu\text{m}$, or smaller

Dynamic range : 8, 12, 14 or 16 bits

Scintillator : YAG or phosphors (thickness is important)

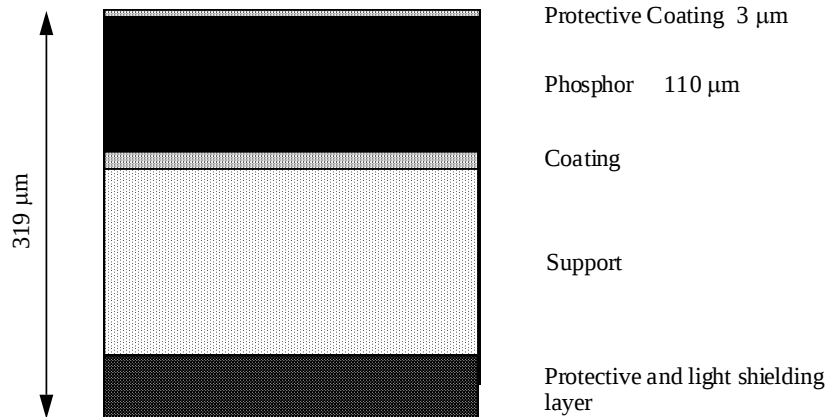
Optical couplings : optical fiber or lens

CCD : pixel size, dark current and readout noise



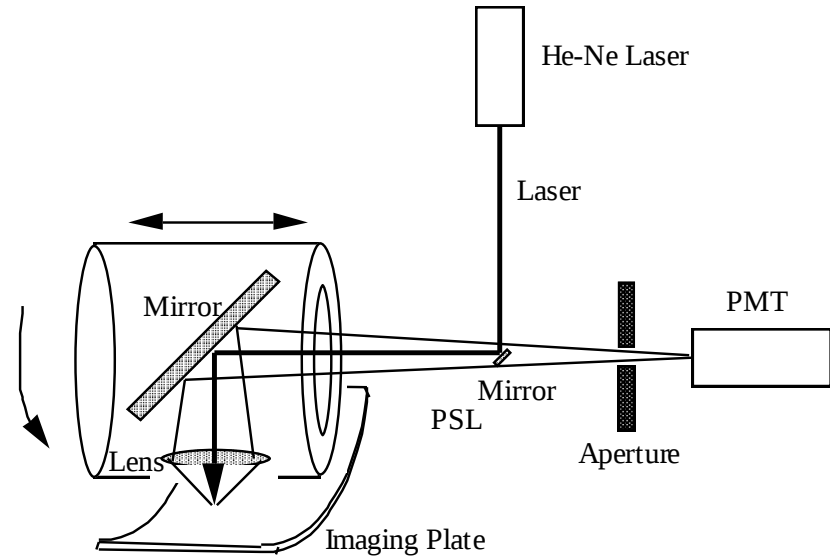
Imaging Plates:

Record like a film



Usable area : 75x94 mm², 3000x3750
pixels (25 μm)
Dynamic range : $10^4 \sim 10^5$

Readout like a digitizer



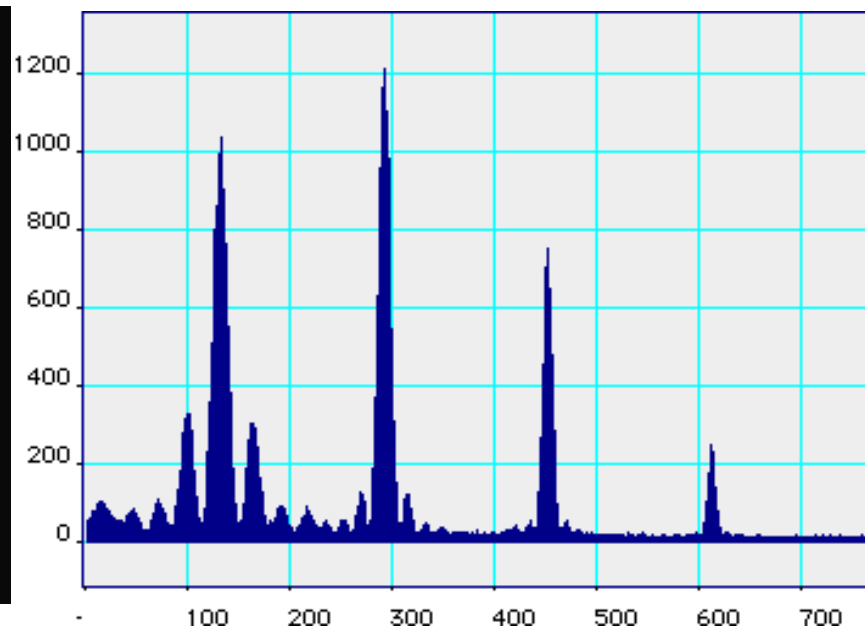
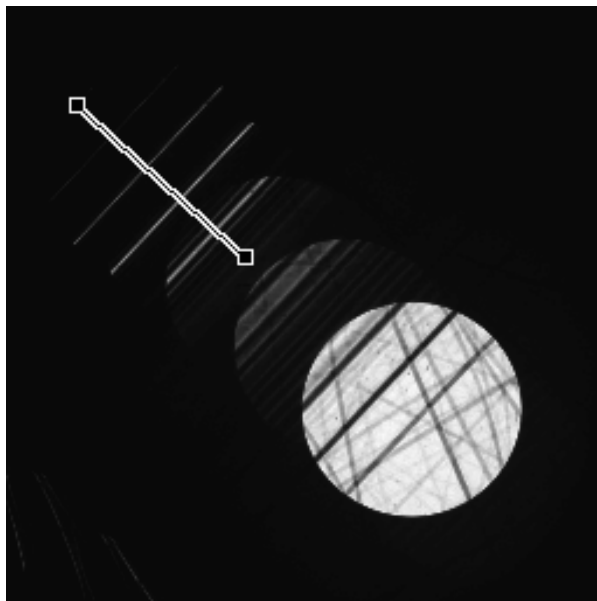
Reader :

- 19 μm laser spot
- Serial scan
- Photomultiplier for detecting photons

As-recorded CBED patterns by the SSC and IP. The large background in the CCD is due the long tail in the point spread function (PSF).

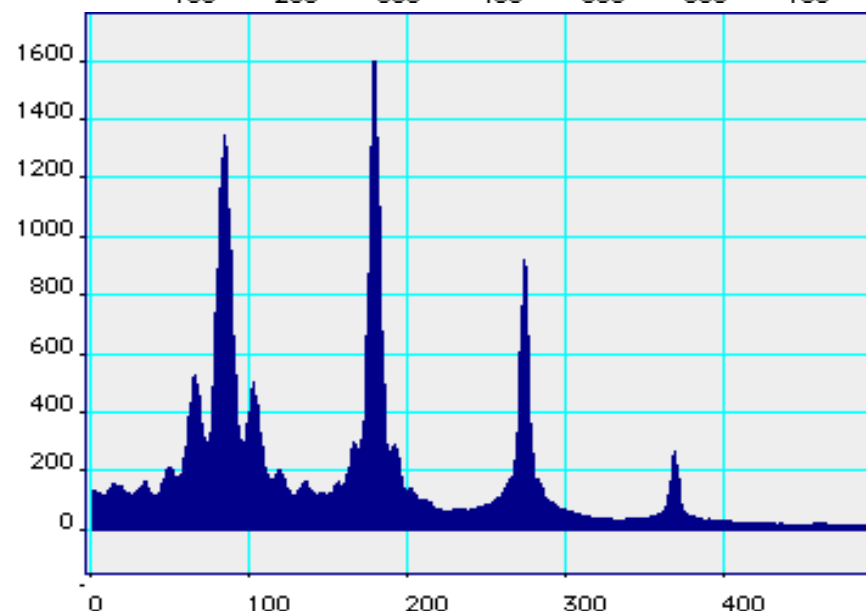
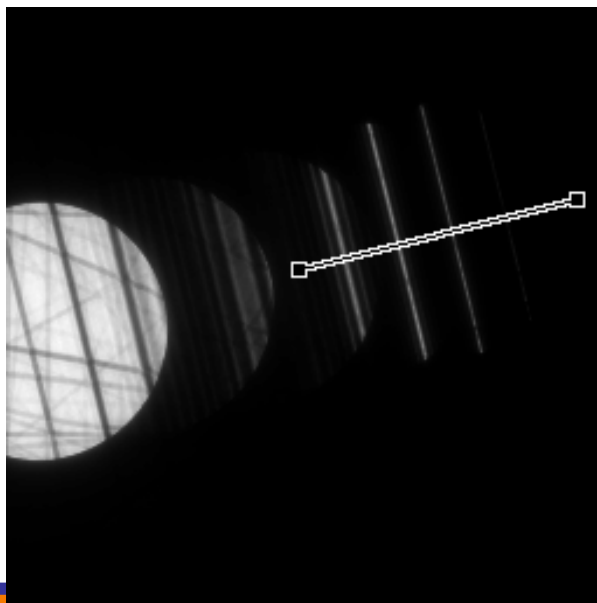
IP

(2048x
2048)



CCD

(1024x
1024)

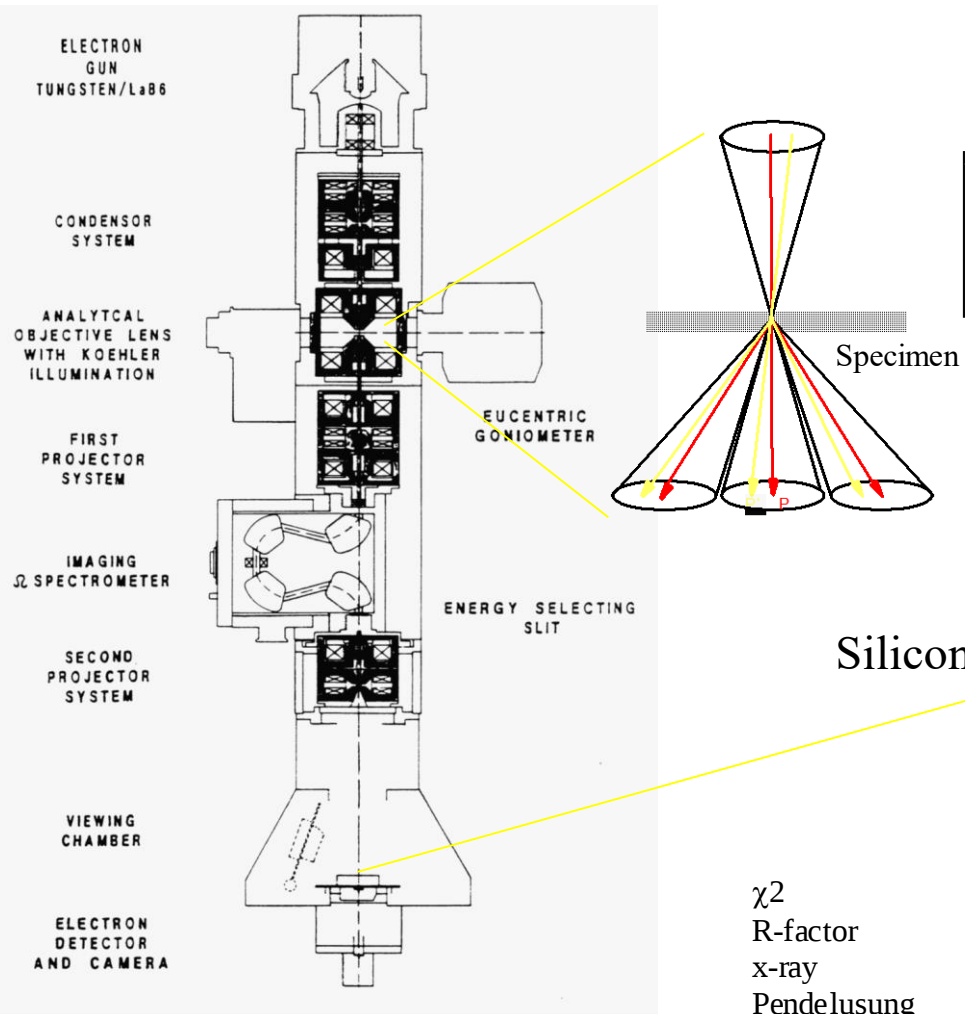


Electron Diffraction Refinement

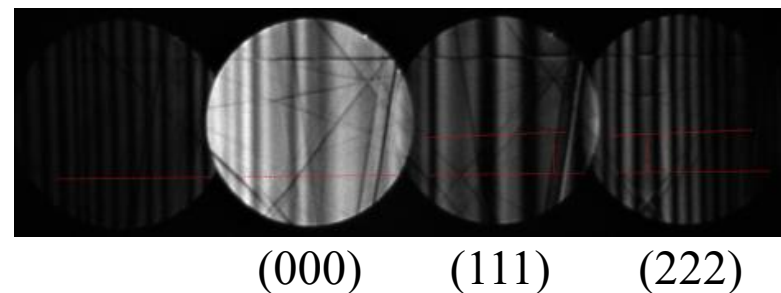
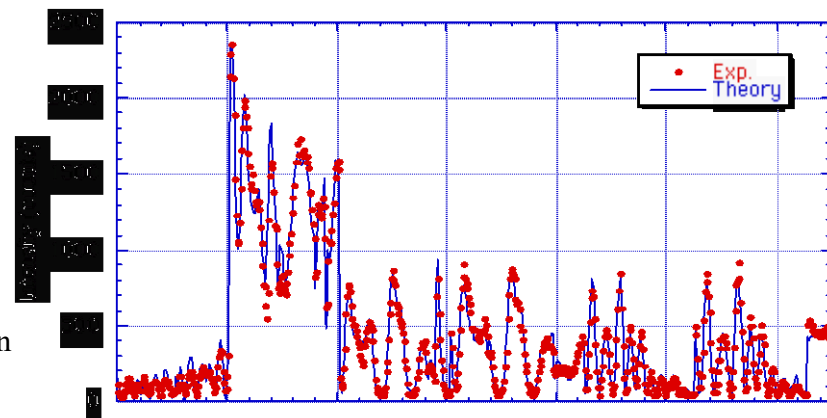
$$\chi^2 = \frac{1}{n - p} \sum_{i=1, \dots, n} \frac{1}{\sigma_i^2} \left(I_i^{\text{exp}} - I_i^{\text{Theory}} [p_1, p_2, \dots, p_m] \right)^2$$

i for sampled points inside CBED disks

Structure factor measurement using electron diffraction



Structure Factor Refinement



χ^2	U(111)	U'(111)	U(222)	GOF
R-factor	0.04735	0.00086	0.00093	4.2
x-ray	0.04731	0.00084	0.00092	0.096
Pendelung	0.04736(4)		0.000943(5)	

Pixel Array Detector

Diode Detection Layer

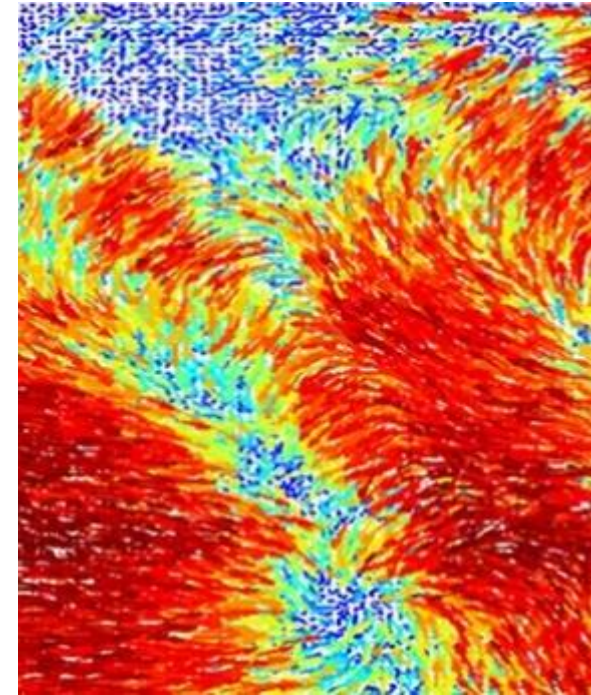
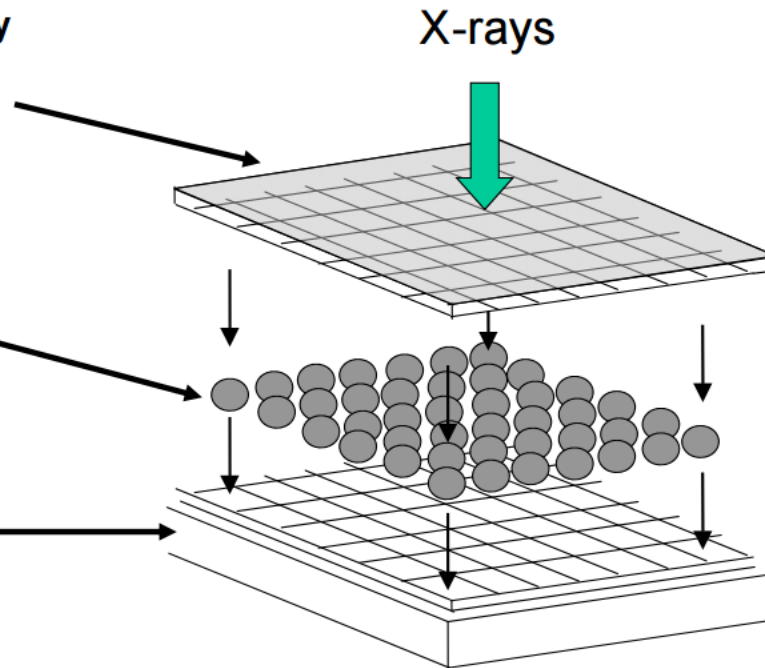
- Fully depleted, high resistivity
- Direct x-ray conversion in Si

Hybridized with Connecting Bumps

- Solder, 1 per pixel

CMOS Layer

- Signal processing
- Signal storage & output



From Cornell, Sol Gruner



Electron beam
 $10^1 \sim 10^2$ keV

Charging

Beam heating

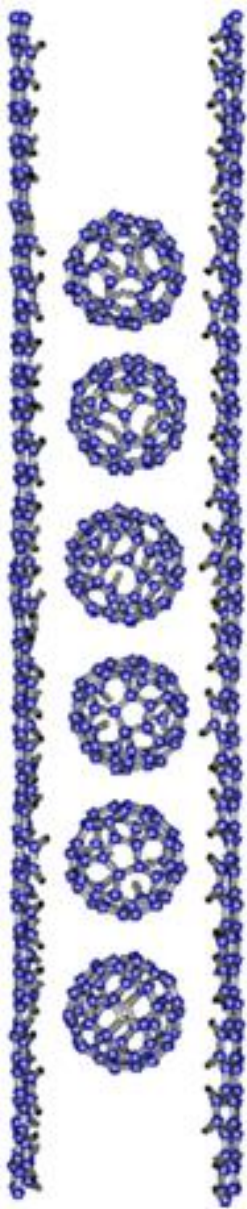
Atomic displacement

Sputtering

Frenkel Pair

R.F. Egerton et al., *Micron* 35 (2004) 399–409

Carbon “Peapods” C60@CNT



K. Ran, J. M. Zuo, Q. Chen, and Z. J. Shi, "Electron Beam Stimulated Molecular Motions," *Acs Nano* 5 (4), 3367-3372 (2011)